

C E R T I F I C A T I O N

I, Takashi KOJIMA of Ginza Ohtsuka Bldg., 2F, 16-12, Ginza 2-chome, Chuo-ku, Tokyo, Japan, hereby certify that I am the translator of the accompanying certified official copy of the documents in respect of an application for a patent filed in Japan on the 10th of February, 2003 and of the official certificate attached thereto, and certify that the following is a true and correct translation to the best of my knowledge and belief.

Dated this 13th day of February, 2006


Takashi KOJIMA



(Translation)

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Central Glass Co., Ltd.

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[List of Documents Attached]
[Document] Specification 1
[Document] Abstract 1

[Necessity of Proof] Yes

2003-032584

[SPECIFICATION]

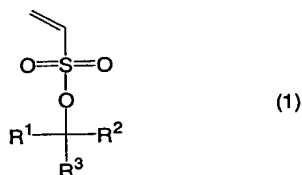
[TITLE OF THE INVENTION] Sulfonate compound, Polymers,
Resist Compositions and Patterning
Process

5

[CLAIMS]

[Claim 1] A sulfonate compound having the following
general formula (1):

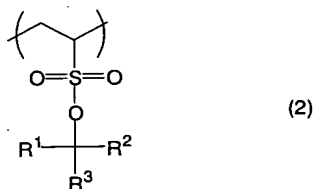
[Formula 1]



10 wherein R¹ to R³ each are hydrogen, fluorine or a straight,
branched or cyclic alkyl or fluorinated alkyl group of 1 to
20 carbon atoms, at least one of R¹ to R³ contains fluorine,
R¹ and R², R¹ and R³, or R² and R³, taken together, may form a
ring, each of R¹ to R³ is a straight or branched alkylene or
15 fluorinated alkylene group of 1 to 18 carbon atoms,
preferably 1 to 10 carbon atoms, when they form a ring.

[Claim 2] A polymer comprising recurring units of the
following general formula (2) and having a weight average
molecular weight of 1,000 to 500,000,

20 [Formula 2]

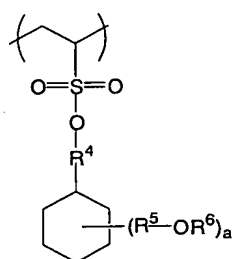


wherein R¹ to R³ each are hydrogen, fluorine or a straight,
branched or cyclic alkyl or fluorinated alkyl group of 1 to
20 carbon atoms, at least one of R¹ to R³ contains fluorine,
R¹ and R², R¹ and R³, or R² and R³, taken together, may form a
25 ring, each of R¹ to R³ is a straight or branched alkylene or

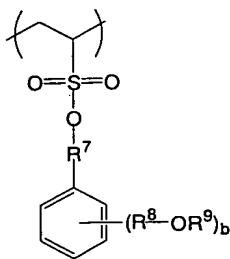
fluorinated alkylene group of 1 to 18 carbon atoms, preferably 1 to 10 carbon atoms, when they form a ring.

[Claim 3] The polymer of claim 2, further comprising recurring units of at least one type selected from the following general formulae (3a) to (3f):

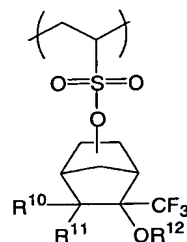
[Formula 3]



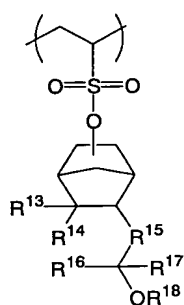
(3a)



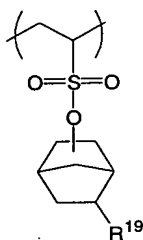
(3b)



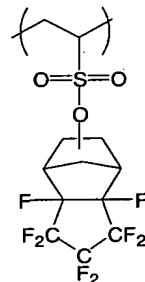
(3c)



(3d)



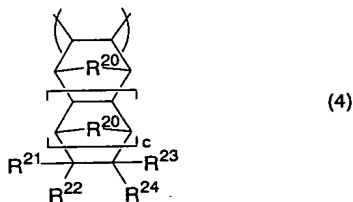
(3e)



(3f)

wherein R^4 , R^5 , R^7 , R^8 and R^{15} each are a single bond or a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms, R^6 , R^9 , R^{12} and R^{18} each are hydrogen or an acid labile group, R^{10} , R^{11} , R^{13} , R^{14} , R^{16} and R^{17} each are hydrogen, fluorine, a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, at least one of R^{16} and R^{17} contains at least one fluorine atom, R^{19} is a straight, branched or cyclic fluorinated alkyl group of 1 to 20 carbon atoms, "a" and "b" each are 1 or 2.

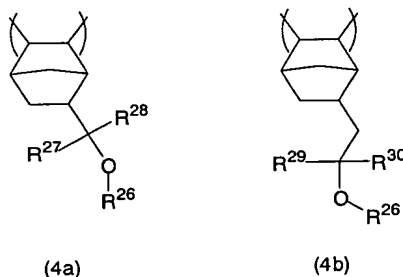
[Formula 4]



5 wherein R²⁰ is a methylene group, oxygen atom or sulfur atom, R²¹ to R²⁴ each are hydrogen, fluorine, -R²⁵-OR²⁶, -R²⁵-CO₂R²⁶ or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, at least one of R²¹ to R²⁴ containing -R²⁵-OR²⁶ or -R²⁵-CO₂R²⁶, R²⁵ is a single bond or a
10 straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms, R²⁶ is hydrogen, an acid labile group, adhesive group or a straight, branched or cyclic fluorinated alkyl group of 1 to 20 carbon atoms which may contain a hydrophilic group such as hydroxyl, and c is 0
15 or 1.

[Claim 5] The polymer of claim 4 wherein said recurring units of formula (4) have a structure of the following general formula (4a) or (4b):

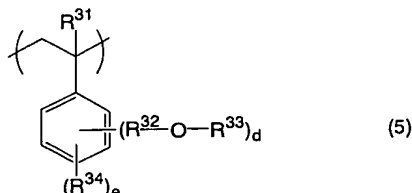
[Formula 5]



20 wherein R²⁶ is as defined above, R²⁷ to R³⁰ each are hydrogen, fluorine or an alkyl or fluorinated alkyl group of 1 to 4 carbon atoms, at least either one of R²⁷ and R²⁸ contains at least one fluorine atom, and at least either one of R²⁹ and R³⁰ contains at least one fluorine atom.

[Claim 6] The polymer of any one of claims 2 to 5, further comprising recurring units of the following general formula (5):

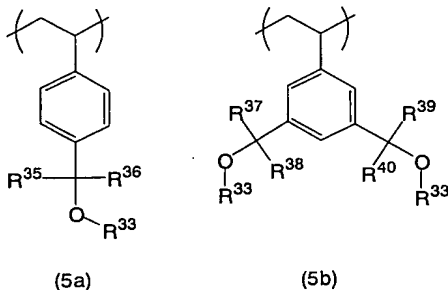
[Formula 6]



5 wherein R^{31} is hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, R^{32} is a single bond or a straight, branched or cyclic
alkylene or fluorinated alkylene group of 1 to 20 carbon
atoms, R^{33} is hydrogen or an acid labile group, R^{34} is
10 fluorine or a straight, branched or cyclic fluorinated alkyl
group of 1 to 20 carbon atoms, d is 1 or 2, and e is an
integer of 0 to 4, satisfying $1 \leq d+e \leq 5$.

[Claim 7] The polymer of claim 6 wherein the recurring
units of formula (5) have the following formula (5a) or
15 (5b):

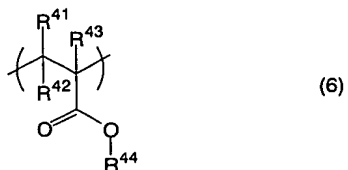
[Formula 7]



wherein R^{33} is as defined above, R^{35} to R^{40} each are hydrogen,
fluorine or an alkyl or fluorinated alkyl group of 1 to 4
20 carbon atoms, at least either one of R^{35} and R^{36} contains at
least one fluorine atom, at least either one of R^{37} and R^{38}
contains at least one fluorine atom, and at least either one
of R^{39} and R^{40} contains at least one fluorine atom.

[Claim 8] The polymer of any one of claims 2 to 7, further comprising recurring units of the following general formula (6):

[Formula 8]



5 wherein R⁴¹ to R⁴³ each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, and R⁴⁴ is hydrogen, an acid labile group, an adhesive group or a straight, branched or cyclic
10 fluorinated alkyl group of 1 to 20 carbon atoms which may contain a hydrophilic group such as hydroxyl.

[Claim 9] The polymer of claim 8 wherein R⁴³ in formula (6) is trifluoromethyl.

[Claim 10] A resist composition comprising the polymer of
15 any one of claims 2 to 9.

[Claim 11] A chemically amplified positive resist composition comprising

- 20 (A) the polymer of any one of claims 2 to 9,
(B) an organic solvent, and
(C) a photoacid generator.

[Claim 12] The resist composition of claim 11, further comprising a basic compound.

[Claim 13] The resist composition of claim 11 or 12, further comprising a dissolution inhibitor.

25 [Claim 14] A process for forming a resist pattern comprising the steps of:

- (1) applying the resist composition of any one of claims 10 to 13 onto a substrate to form a coating,
(2) heat treating the coating and then exposing it to
30 high-energy radiation in a wavelength band of 100 to 180 nm or 1 to 30 nm through a photomask, and
(3) optionally heat treating the exposed coating and developing it with a developer.

[Claim 15] The pattern forming process of claim 14 wherein the high-energy radiation is an F₂ laser beam, Ar₂ laser beam or soft x-ray.

[DETAILED EXPLANATION OF THE INVENTION]

5 [0001]

[Technical Field of the Invention]

This invention relates to polymers useful as the base resin in resist compositions suited for microfabrication and sulfonic acid esters useful as the starting monomers for the
10 polymers. It also relates to resist compositions, especially chemical amplification resist compositions comprising the polymers, and a patterning process using the same.

[0002]

15 [Prior Art]

In the drive for higher integration and operating speeds in LSI devices, the pattern rule is made drastically finer.

The rapid advance toward finer pattern rules is
20 grounded on the development of a projection lens with an increased NA, a resist material with improved performance, and exposure light of a shorter wavelength. To the demand for a resist material with a higher resolution and sensitivity, chemical amplification positive working resist
25 materials which are catalyzed by acids generated upon light exposure are effective. They now become predominant resist materials especially adapted for deep UV lithography (Patent Document 1, 2: JP-B 2-27660 and JP-A 63-27829).

[0003]

30 Also, the change-over from i-line (365 nm) to shorter wavelength KrF laser (248 nm) brought about a significant innovation. Resist materials adapted for KrF excimer lasers enjoyed early use on the 0.30 micron process, passed through the 0.25 micron rule, and currently entered the mass
35 production phase on the 0.18 micron rule. Engineers have started investigation on the 0.10 micron rule or less, with the trend toward a finer pattern rule being accelerated.

[0004]

For ArF laser (193 nm), it is expected to enable miniaturization of the design rule to 0.13 μm or less. Since conventionally used novolac resins and polyvinylphenol resins have very strong absorption in proximity to 193 nm, they cannot be used as the base resin for resists. To ensure transparency and dry etching resistance, some engineers investigated acrylic and alicyclic (typically cycloolefin) resins. (Patent Document 3-6: JP-A 9-73173, JP-A 10-10739, JP-A 9-230595 and WO 97/33198).

[0005]

With respect to F_2 laser (157 nm) which is expected to enable further miniaturization to 0.10 μm or less, more difficulty arises in insuring transparency because it was found that acrylic resins which are used as the base resin for ArF are not transmissive to light at all and those cycloolefin resins having carbonyl bonds have strong absorption. It was also found that poly(vinyl phenol) which is used as the base resin for KrF has a window for absorption in proximity to 160 nm, so the transmittance is somewhat improved, but far below the practical level.

[0006]

Since carbonyl groups and carbon-to-carbon double bonds have absorption in proximity to 157 nm as mentioned above, reducing the number of such units is contemplated to be one effective way for improving transmittance. It was recently found that the transmittance in the F_2 region is outstandingly improved by introducing fluorine atoms into base polymers.

[0007]

It was reported in SPIE 2001, Proceedings 4345-31, "Polymer design for 157 nm chemically amplified resists" (Non Patent Document 1) that in resist compositions comprising a copolymer of tert-butyl α -trifluoromethylacrylate with 5-(2-hydroxy-2,2-bistrifluoromethyl)ethyl-2-norbornene and

a copolymer of tert-butyl α -trifluoromethylacrylate with
4-(2-hydroxy-2,2-bistrifluoromethyl)methylstyrene, the
absorbance of the polymer at 157 nm is improved to about 3.
However, these resins are still insufficient in transparency
5 because it is believed that an absorbance of 2 or less is
necessary to form a rectangular pattern at a film thickness
of at least 2,000 Å through F₂ exposure.

[0008]

The inventor have been earnestly studied and found
10 that incorporating fluorinated vinyl sulfonate units into
the above-described α -trifluoromethylacrylate polymers
improves the transparency while maintaining the substrate
adhesion and developer affinity of the resins. These
systems still have an absorbance of approximately 2.

15 [0009]

[Patent Document 1]

JP-B 2-27660

[Patent Document 2]

JP-A 63-27829

20 [Patent Document 3]

JP-A 9-73173

[Patent Document 4]

JP-A 10-10739

[Patent Document 5]

25 JP-A 9-230595

[Patent Document 6]

WO 97/33198

[Patent Document 7]

JP-A 2001-146505

30 [Non-Patent Document 1]

SPIE 2001, Proceedings 4345-31

[0010]

[Problem to be Solved by the Invention]

The present invention has been done in view of the
35 above circumstances. An object of the invention is to
provide a novel polymer having a high transmittance to
vacuum ultraviolet radiation of up to 300 nm, especially F₂

(157 nm), Kr₂ (146 nm), KrAr (134 nm) and Ar₂ (126 nm) laser beams, and useful as the base resin in a resist composition, and a novel sulfonic acid ester useful as the starting monomer for the polymer. Another object is to provide a
5 resist composition, especially a chemical amplification resist composition, comprising the polymer, and a patterning process using the same.

[0011]

[Means for Solving the Problem and Embodiment of the
10 Invention]

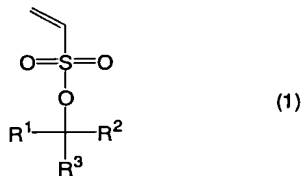
The present inventors have earnestly studied in order to attain the above object. As a result, it has been found that when a polymer comprising units derived from a monomer having a fluorinated alkyl group introduced on a sulfonate
15 side chain is used as a base resin, the resulting resist composition, especially chemically amplified resist composition is drastically improved in contrast and adhesion without detracting from transparency. Thus, the present invention has been completed.

20 [0012]

The present invention provides a following polymer, resist composition and patterning process.

Claim 1: A sulfonate compound having the following general formula (1):

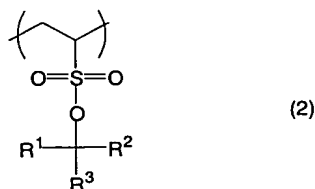
25 [Formula 9]



wherein R¹ to R³ each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, at least one of R¹ to R³ contains fluorine, R¹ and R², R¹ and R³, or R² and R³, taken together, may form a
30 ring, each of R¹ to R³ is a straight or branched alkylene or fluorinated alkylene group of 1 to 18 carbon atoms, preferably 1 to 10 carbon atoms, when they form a ring.

Claim 2: A polymer comprising recurring units of the following general formula (2) and having a weight average molecular weight of 1,000 to 500,000,

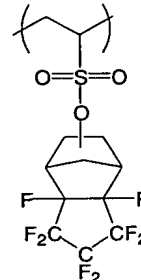
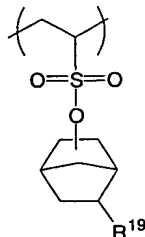
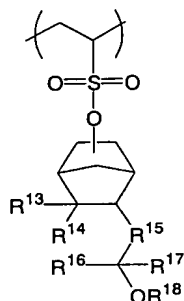
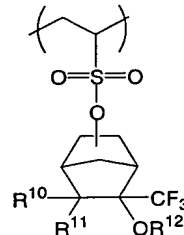
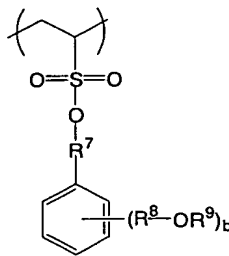
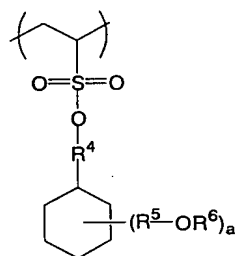
[Formula 10]



5 wherein R^1 to R^3 each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, at least one of R^1 to R^3 contains fluorine, R^1 and R^2 , R^1 and R^3 , or R^2 and R^3 , taken together, may form a ring, each of R^1 to R^3 is a straight or branched alkylene or
 10 fluorinated alkylene group of 1 to 18 carbon atoms, preferably 1 to 10 carbon atoms, when they form a ring.

Claim 3: The polymer of claim 2, further comprising recurring units of at least one type selected from the following general formulae (3a) to (3f):

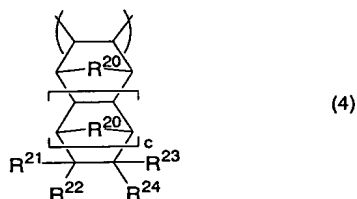
15 [Formula 11]



wherein R^4 , R^5 , R^7 , R^8 and R^{15} each are a single bond or a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms, R^6 , R^9 , R^{12} and R^{18} each are hydrogen or an acid labile group, R^{10} , R^{11} , R^{13} , R^{14} , R^{16} and R^{17} each are hydrogen, fluorine, a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, at least one of R^{16} and R^{17} contains at least one fluorine atom, R^{19} is a straight, branched or cyclic fluorinated alkyl group of 1 to 20 carbon atoms, "a" and "b" each are 1 or 2.

Claim 4: The polymer of claim 2 or 3, further comprising recurring units of the following general formula (4):

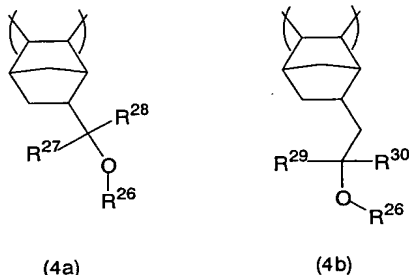
[Formula 12]



wherein R^{20} is a methylene group, oxygen atom or sulfur atom, R^{21} to R^{24} each are hydrogen, fluorine, $-R^{25}-OR^{26}$, $-R^{25}-CO_2R^{26}$ or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, at least one of R^{21} to R^{24} containing $-R^{25}-OR^{26}$ or $-R^{25}-CO_2R^{26}$, R^{25} is a single bond or a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms, R^{26} is hydrogen, an acid labile group, adhesive group or a straight, branched or cyclic fluorinated alkyl group of 1 to 20 carbon atoms which may contain a hydrophilic group such as hydroxyl, and c is 0 or 1.

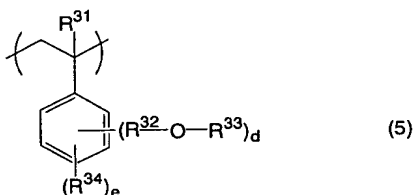
Claim 5: The polymer of claim 4 wherein said recurring units of formula (4) have a structure of the following general formula (4a) or (4b):

[Formula 13]



- 5 wherein R^{26} is as defined above, R^{27} to R^{30} each are hydrogen, fluorine or an alkyl or fluorinated alkyl group of 1 to 4 carbon atoms, at least either one of R^{27} and R^{28} contains at least one fluorine atom, and at least either one of R^{29} and R^{30} contains at least one fluorine atom.
- 10 Claim 6: The polymer of any one of claims 2 to 5, further comprising recurring units of the following general formula (5):

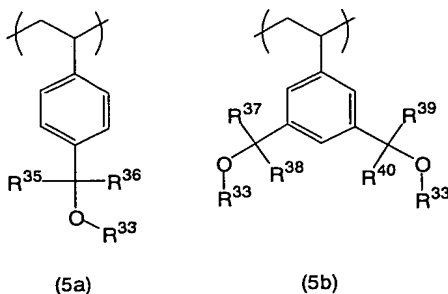
[Formula 14]



- 15 wherein R^{31} is hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, R^{32} is a single bond or a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms, R^{33} is hydrogen or an acid labile group, R^{34} is fluorine or a straight, branched or cyclic fluorinated alkyl
- 20 group of 1 to 20 carbon atoms, d is 1 or 2, and e is an integer of 0 to 4, satisfying $1 \leq d+e \leq 5$.

Claim 7: The polymer of claim 6 wherein the recurring units of formula (5) have the following formula (5a) or (5b):

[Formula 15]



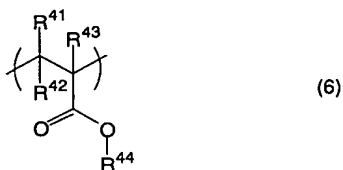
5

wherein R^{33} is as defined above, R^{35} to R^{40} each are hydrogen, fluorine or an alkyl or fluorinated alkyl group of 1 to 4 carbon atoms, at least either one of R^{35} and R^{36} contains at least one fluorine atom, at least either one of R^{37} and R^{38} contains at least one fluorine atom, and at least either one of R^{39} and R^{40} contains at least one fluorine atom.

10

Claim 8: The polymer of any one of claims 2 to 7, further comprising recurring units of the following general formula (6):

15 [Formula 16]



20

wherein R^{41} to R^{43} each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, and R^{44} is hydrogen, an acid labile group, an adhesive group or a straight, branched or cyclic fluorinated alkyl group of 1 to 20 carbon atoms which may contain a hydrophilic group such as hydroxyl.

Claim 9: The polymer of claim 8 wherein R^{43} in formula (6) is trifluoromethyl.

25

Claim 10: A resist composition comprising the polymer of any one of claims 2 to 9.

Claim 11: A chemically amplified positive resist composition comprising

- (A) the polymer of any one of claims 2 to 9,
- (B) an organic solvent, and
- 5 (C) a photoacid generator.

Claim 12: The resist composition of claim 11, further comprising a basic compound.

Claim 13: The resist composition of claim 11 or 12, further comprising a dissolution inhibitor.

10 Claim 14: A process for forming a resist pattern comprising the steps of:

- (1) applying the resist composition of any one of claims 10 to 13 onto a substrate to form a coating,
- (2) heat treating the coating and then exposing it to
- 15 high-energy radiation in a wavelength band of 100 to 180 nm or 1 to 30 nm through a photomask, and
- (3) optionally heat treating the exposed coating and developing it with a developer.

Claim 15: The pattern forming process of claim 14 wherein

20 the high-energy radiation is an F₂ laser beam, Ar₂ laser beam or soft x-ray.

[0013]

The following is the detailed description of the present invention.

25 The inventors have found that for improving the transmittance in proximity to 157 nm, reducing the number of carbonyl groups and/or carbon-to-carbon double bonds is contemplated to be one effective way. It was also found that introducing fluorine atoms into base polymers makes a

30 great contribution to improved transmittance. In fact, poly(vinyl phenol) having fluorine introduced in its aromatic rings offers a transmittance nearly on a practically acceptable level (Patent Document 7: JP-A 2001-146505). However, this base polymer was found to turn

35 to be negative upon exposure to high-energy radiation as from an F₂ laser, interfering with its use as a practical resist. On the other hand, those polymers obtained by

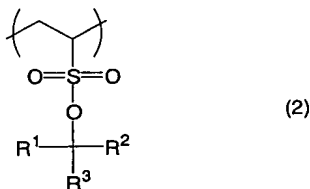
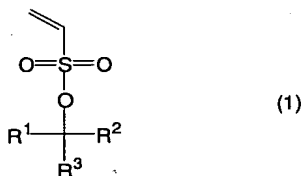
introducing fluorine into acrylic resins or polymers containing in their backbone an alicyclic compound originating from a norbornene derivative were found to have a high transparency and eliminate the negative turning problem. However, an increased rate of introduction of fluorine into a resin to enhance the transparency thereof tends to compromise the adhesion of resin to substrate or the penetration of a developer.

[0014]

It has been found that sulfonates have a relatively high transmittance at about 157 nm despite two sulfur-oxygen double bonds, and a resin comprising such sulfonate units is dramatically improved in substrate adhesion and developer penetration as compared with the aforementioned fluorinated polymers. Specifically, in the present invention, using a base polymer comprising units of the general formula (2) derived from a sulfonate compound of the general formula (1) which is obtained by introducing fluorine into a tertiary alkyl ester of sulfonic acid which inherently lacks stability, a resist composition having an acid eliminating ability is obtained while maintaining stability.

[0015]

[Formula 17]



Herein R^1 to R^3 each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, at least one of R^1 to R^3 contains fluorine,

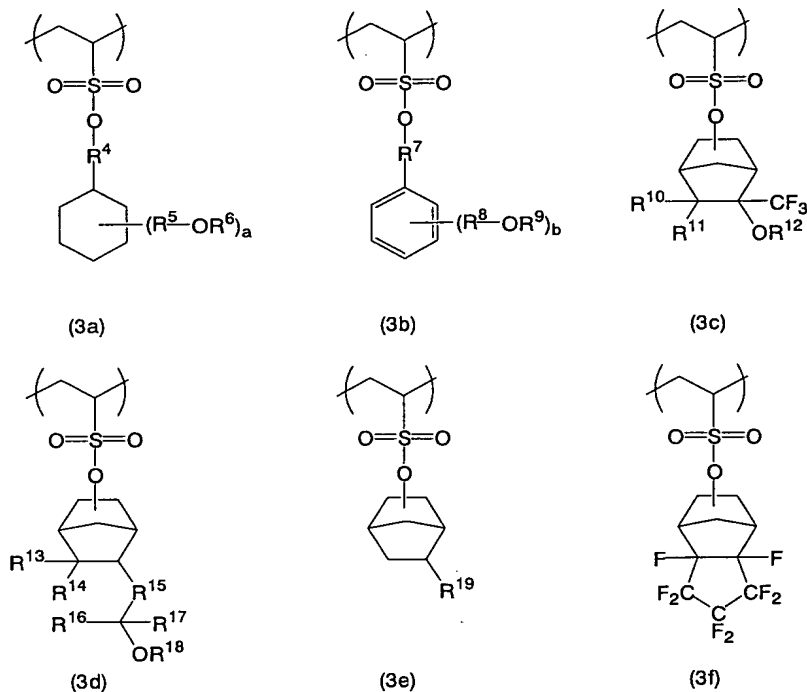
a pair of R^1 and R^2 , a pair of R^1 and R^3 , or a pair of R^2 and R^3 , taken together, may form a ring, each of R^1 to R^3 is a straight or branched alkylene or fluorinated alkylene group of 1 to 18 carbon atoms, preferably 1 to 10 carbon atoms, when they form a ring.

[0016]

While the polymer or high molecular weight compound of the invention is defined as comprising recurring units of the general formula (2), recurring units of at least one type selected from the general formulae (3a) to (3f) and/or recurring units of the general formula (4) and/or recurring units of the general formula (5) and/or recurring units of the general formula (6) are preferably incorporated in order to improve the dissolution contrast, substrate adhesion, dry etching resistance and other properties of the resist.

[0017]

[Formula 18]

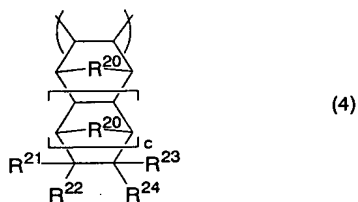


Herein R^4 , R^5 , R^7 , R^8 and R^{15} each are a single bond or a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms, R^6 , R^9 , R^{12} and R^{18}

each are hydrogen or an acid labile group, R^{10} , R^{11} , R^{13} , R^{14} , R^{16} and R^{17} each are hydrogen, fluorine, a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, at least one of R^{16} and R^{17} contains at least one
 5 fluorine atom, R^{19} is a straight, branched or cyclic fluorinated alkyl group of 1 to 20 carbon atoms, "a" and "b" each are 1 or 2.

[0018]

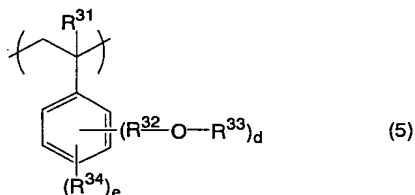
[Formula 19]



10 Herein R^{20} is a methylene group, oxygen atom or sulfur atom, R^{21} to R^{24} each are hydrogen, fluorine, $-R^{25}-OR^{26}$, $-R^{25}-CO_2R^{26}$ or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, at least one of R^{21} to R^{24} containing $-R^{25}-OR^{26}$ or $-R^{25}-CO_2R^{26}$, R^{25} is a single bond or a
 15 straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms, R^{26} is hydrogen, an acid labile group, adhesive group or a straight, branched or cyclic fluorinated alkyl group of 1 to 20 carbon atoms which may contain a hydrophilic group such as hydroxyl, and c is 0
 20 or 1.

[0019]

[Formula 20]

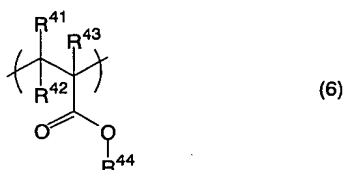


Herein R^{31} is hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, R^{32} is a single bond or a straight, branched or cyclic
 25 alkylene or fluorinated alkylene group of 1 to 20 carbon

atoms, R^{33} is hydrogen or an acid labile group, R^{34} is fluorine or a straight, branched or cyclic fluorinated alkyl group of 1 to 20 carbon atoms, d is 1 or 2, and e is an integer of 0 to 4, satisfying $1 \leq d+e \leq 5$.

5 [0020]

[Formula 21]

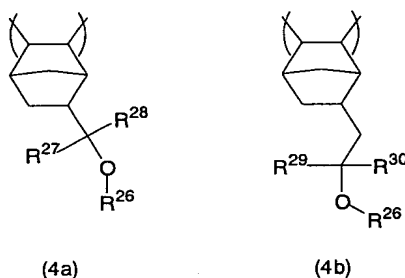


Herein R^{41} to R^{43} each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, and R^{44} is hydrogen, an acid labile group, an adhesive group or a straight, branched or cyclic fluorinated alkyl group of 1 to 20 carbon atoms which may contain a hydrophilic group such as hydroxyl. Preferably, R^{43} is trifluoromethyl.

15 [0021]

The preferred recurring units of formula (4) are units of the following general formula (4a) or (4b).

[Formula 22]

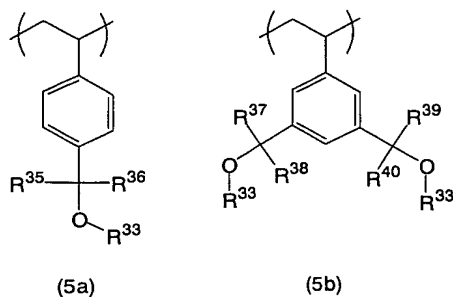


Herein R^{26} is as defined above, R^{27} to R^{30} each are hydrogen, fluorine or an alkyl or fluorinated alkyl group of 1 to 4 carbon atoms, at least either one of R^{27} and R^{28} contains at least one fluorine atom, and at least either one of R^{29} and R^{30} contains at least one fluorine atom.

[0022]

25 The preferred recurring units of formula (5) are units of the following formula (5a) or (5b).

[Formula 23]



Herein R³³ is as defined above, R³⁵ to R⁴⁰ each are hydrogen, fluorine or an alkyl or fluorinated alkyl group of 1 to 4 carbon atoms, at least either one of R³⁵ and R³⁶ contains at least one fluorine atom, at least either one of R³⁷ and R³⁸ contains at least one fluorine atom, and at least either one of R³⁹ and R⁴⁰ contains at least one fluorine atom.

[0023]

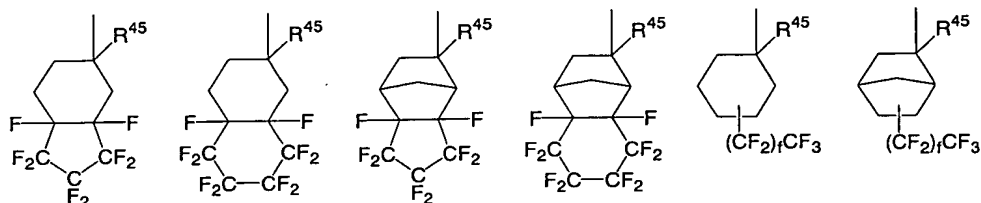
In this case, suitable straight, branched or cyclic alkyl groups of 1 to 20 carbon atoms include, methyl, ethyl, propyl, isopropyl, n-propyl, n-butyl, sec-butyl, tert-butyl, cyclopentyl, cyclohexyl, cyclohexylmethyl, 2-ethylhexyl, n-octyl, 2-adamantyl, and (2-adamantyl)methyl, with those of 1 to 12 carbon atoms, especially 1 to 10 carbon atoms being preferred.

[0024]

The fluorinated alkyl groups correspond to the foregoing alkyl groups in which some or all of the hydrogen atoms are replaced by fluorine atoms. Examples include, trifluoromethyl, 2,2,2-trifluoroethyl, 3,3,3-trifluoropropyl, 1,1,1,3,3,3-hexafluoroisopropyl, and 1,1,2,2,3,3,3-heptafluoropropyl as well as groups of the following formulae.

[0025]

[Formula 24]



Herein, R^{45} is a hydrogen atom, a fluorine atom or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 10 carbon atoms, and f is an integer of 0 to 5.

[0026]

Suitable straight, branched or cyclic alkylene groups of 1 to 20 carbon atoms correspond to the foregoing alkyl groups with one hydrogen atom eliminated. Suitable fluorinated alkylene groups are similar alkylene groups which are partially or entirely substituted with fluorine atoms.

[0027]

The acid labile groups represented by R^6 , R^9 , R^{12} , R^{18} , R^{26} , R^{33} and R^{44} are selected from a variety of such groups, preferably from among the groups of the following general formulae (7) to (9).

[0028]

[Formula 25]



[0029]

In formula (7), R^{46} is a tertiary alkyl group of 4 to 20 carbon atoms, preferably 4 to 15 carbon atoms, or an oxoalkyl group of 4 to 20 carbon atoms. Suitable tertiary
5 alkyl groups include tert-butyl, tert-amyl, 1,1-diethylpropyl, 1-ethylcyclopentyl, 1-butylcyclopentyl, 1-ethylcyclohexyl, 1-butylcyclohexyl, 1-ethyl-2-cyclopentenyl, 1-ethyl-2-cyclohexenyl, and 2-methyl-2-adamantyl. Suitable oxoalkyl groups include
10 3-oxocyclohexyl, 4-methyl-2-oxooxan-4-yl, and 5-methyl-5-oxooxolan-4-yl. Letter g is an integer of 0 to 6.

[0030]

Illustrative, examples of the acid labile group of
15 formula (7) include tert-butoxycarbonyl, tert-butoxycarbonylmethyl, tert-amyloxycarbonyl, tert-amyloxycarbonylmethyl, 1,1-diethylpropyloxycarbonyl, 1,1-diethylpropyloxycarbonylmethyl, 1-ethylcyclopentyloxycarbonyl,
20 1-ethylcyclopentyloxycarbonylmethyl, 1-ethyl-2-cyclopentenylloxycarbonyl, 1-ethyl-2-cyclopentenylloxycarbonylmethyl, 1-ethoxyethoxycarbonylmethyl, 2-tetrahydropyranyloxycarbonylmethyl, and
25 2-tetrahydrofuranyloxycarbonylmethyl groups.

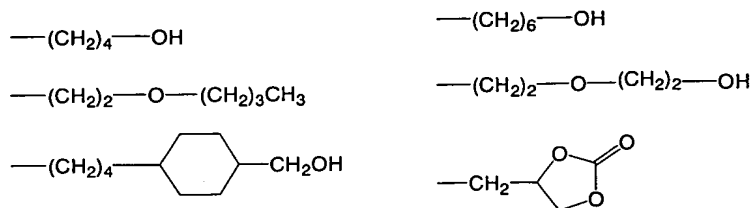
[0031]

In formula (8), R^{47} and R^{48} are hydrogen or straight, branched or cyclic alkyl groups of 1 to 18 carbon atoms, preferably 1 to 10 carbon atoms, for example, methyl, ethyl,
30 propyl, isopropyl, n-butyl, sec-butyl, tert-butyl, cyclopentyl, cyclohexyl, 2-ethylhexyl and n-octyl. R^{49} is a monovalent hydrocarbon group of 1 to 18 carbon atoms, preferably 1 to 10 carbon atoms, which may contain a hetero atom such as oxygen, for example, straight, branched or
35 cyclic alkyl groups and substituted ones of these alkyl groups in which some hydrogen atoms are substituted with

hydroxyl, alkoxy, oxo, amino or alkylamino groups.
Exemplary substituted alkyl groups are shown below.

[0032]

[Formula 26]



5 [0033]

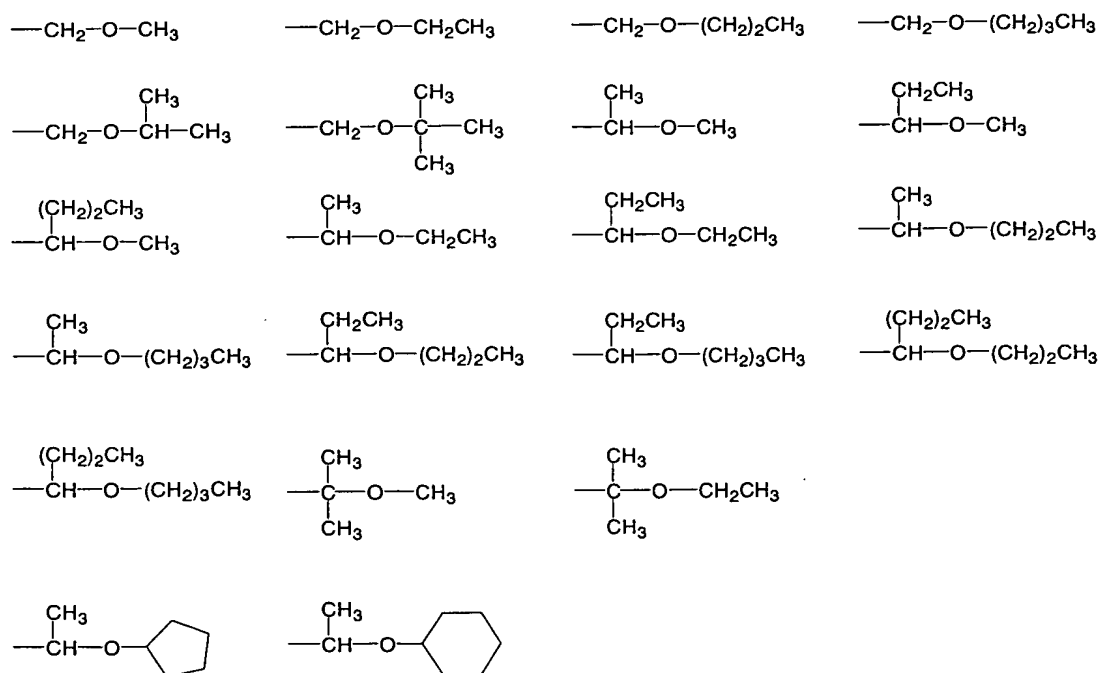
A pair of R^{47} and R^{48} , a pair of R^{47} and R^{49} , or a pair of R^{48} and R^{49} may bond together to form a ring. Each of R^{47} , R^{48} and R^{49} is a straight or branched alkylene group of 1 to 18 carbon atoms, preferably 1 to 10 carbon atoms, when they
10 form a ring.

[0034]

Of the acid labile groups of above formula (8), straight or branched ones are exemplified by the following groups.

15 [0035]

[Formula 27]



[0036]

Of the acid labile groups of formula (8), cyclic ones are exemplified by tetrahydrofuran-2-yl, 2-methyltetrahydrofuran-2-yl, tetrahydropyran-2-yl, and 2-methyltetrahydropyran-2-yl. Of the groups of formula (8), ethoxyethyl, butoxyethyl and ethoxypropyl are preferred.

[0037]

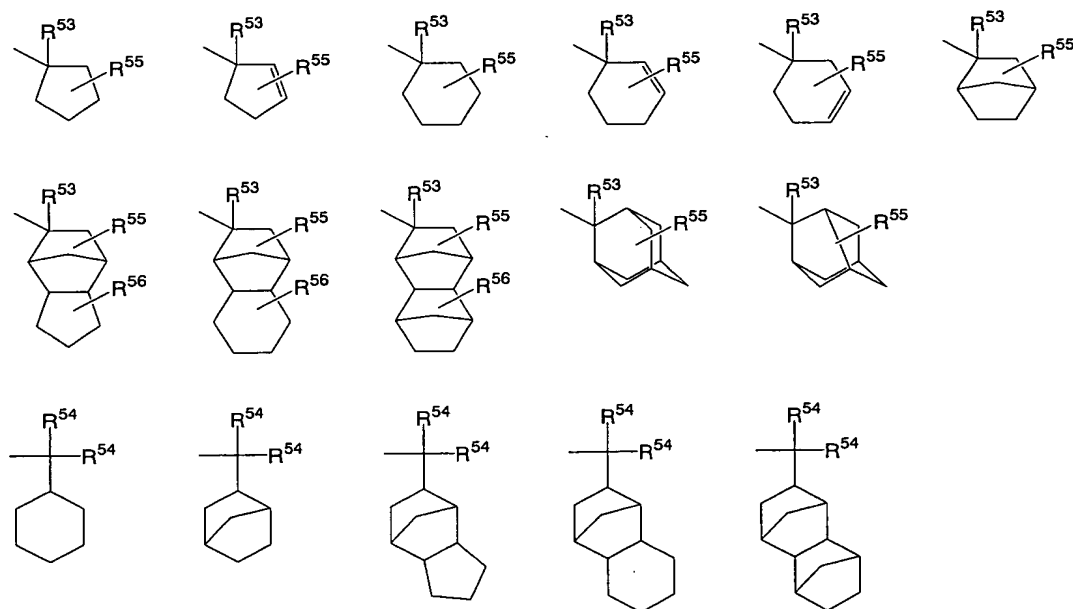
In formula (9), R^{50} , R^{51} and R^{52} each are a monovalent hydrocarbon group, typically a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms, which may contain a hetero atom such as oxygen, sulfur, nitrogen or fluorine. A pair of R^{50} and R^{51} , R^{50} and R^{52} , and R^{51} and R^{52} , taken together, may form a ring with the carbon atom to which they are bonded.

[0038]

Examples of the tertiary alkyl group represented by formula (9) include tert-butyl, triethylcarbyl, 1-ethylnorbornyl, 1-methylcyclohexyl, 1-ethylcyclopentyl, 2-(2-methyl)adamantyl, 2-(2-ethyl)adamantyl, tert-amyl, 1,1,1,3,3,3-hexafluoro-2-methyl-isopropyl, and 1,1,1,3,3,3-hexafluoro-2-cyclohexyl-isopropyl as well as the groups shown below.

[0039]

[Formula 28]



[0040]

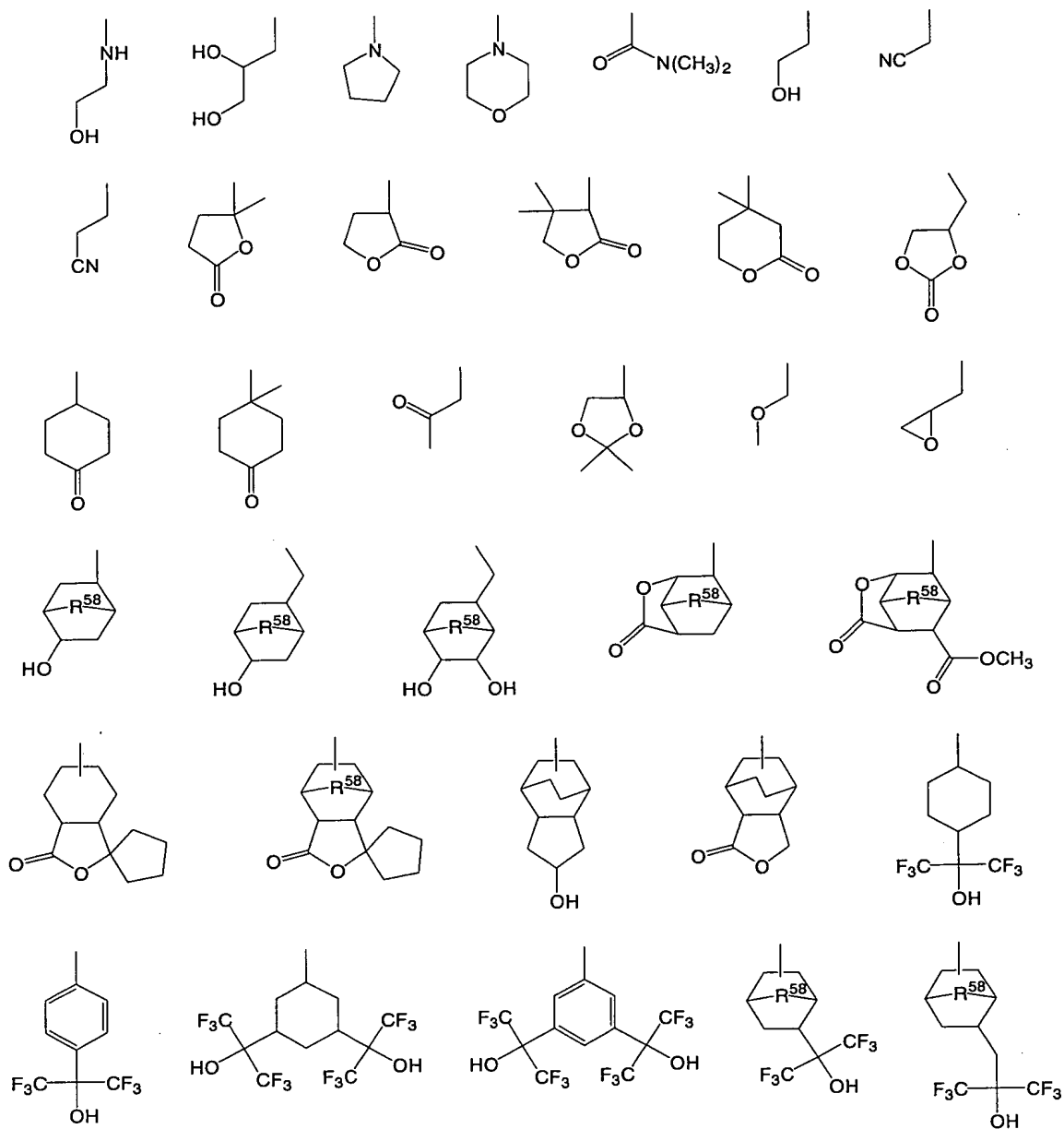
Herein, R^{53} is a straight, branched or cyclic alkyl group of 1 to 6 carbon atoms, such as methyl, ethyl, propyl, isopropyl, n-butyl, sec-butyl, n-pentyl, n-hexyl, cyclopropyl, cyclopropylmethyl, cyclobutyl, cyclopentyl and cyclohexyl. R^{54} is a straight, branched or cyclic alkyl group of 2 to 6 carbon atoms, such as ethyl, propyl, isopropyl, n-butyl, sec-butyl, n-pentyl, n-hexyl, cyclopropyl, cyclopropylmethyl, cyclobutyl, cyclopentyl and cyclohexyl. Each of R^{55} and R^{56} is hydrogen, a monovalent hydrocarbon group of 1 to 6 carbon atoms which may contain a hetero atom, or a monovalent hydrocarbon group of 1 to 6 carbon atoms which may be separated by a hetero atom. These groups may be straight, branched or cyclic. The hetero atom is typically selected from oxygen, sulfur and nitrogen atoms and may be contained or intervene in the form of $-OH$, $-OR^{57}$, $-O-$, $-S-$, $-S(=O)-$, $-NH_2$, $-NHR^{57}$, $-N(R^{57})_2$, $-NH-$ or $-NR^{57}-$ wherein R^{57} is a C_{1-5} alkyl group. Examples of R^{55} and R^{56} groups include methyl, hydroxymethyl, ethyl, hydroxyethyl, propyl, isopropyl, n-butyl, sec-butyl, n-pentyl, n-hexyl, methoxy, methoxymethoxy, ethoxy and tert-butoxy.

[0041]

Next, the adhesive groups represented by R^{26} and R^{44} are selected from a variety of such groups, preferably from among the groups of the following formulae.

[0042]

[Formula 29]



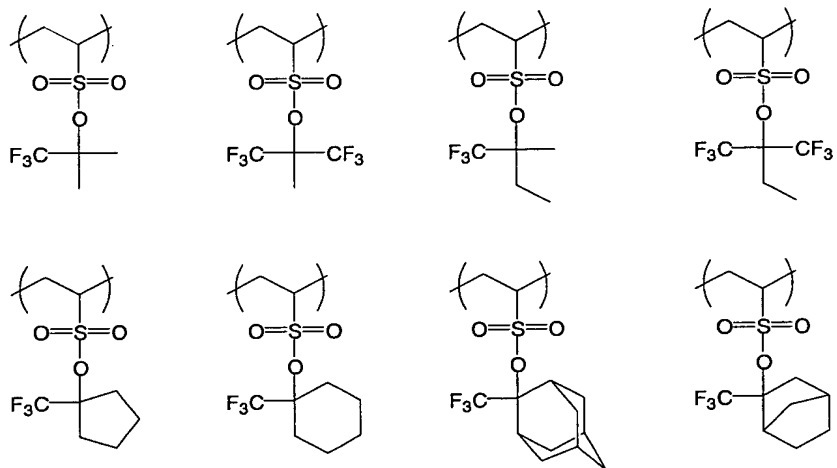
Herein, R^{58} is a methylene group, oxygen atom or sulfur atom.

5 [0043]

Illustrative examples of the units of formula (2) are given below, though not limited thereto.

[0044]

[Formula 30]

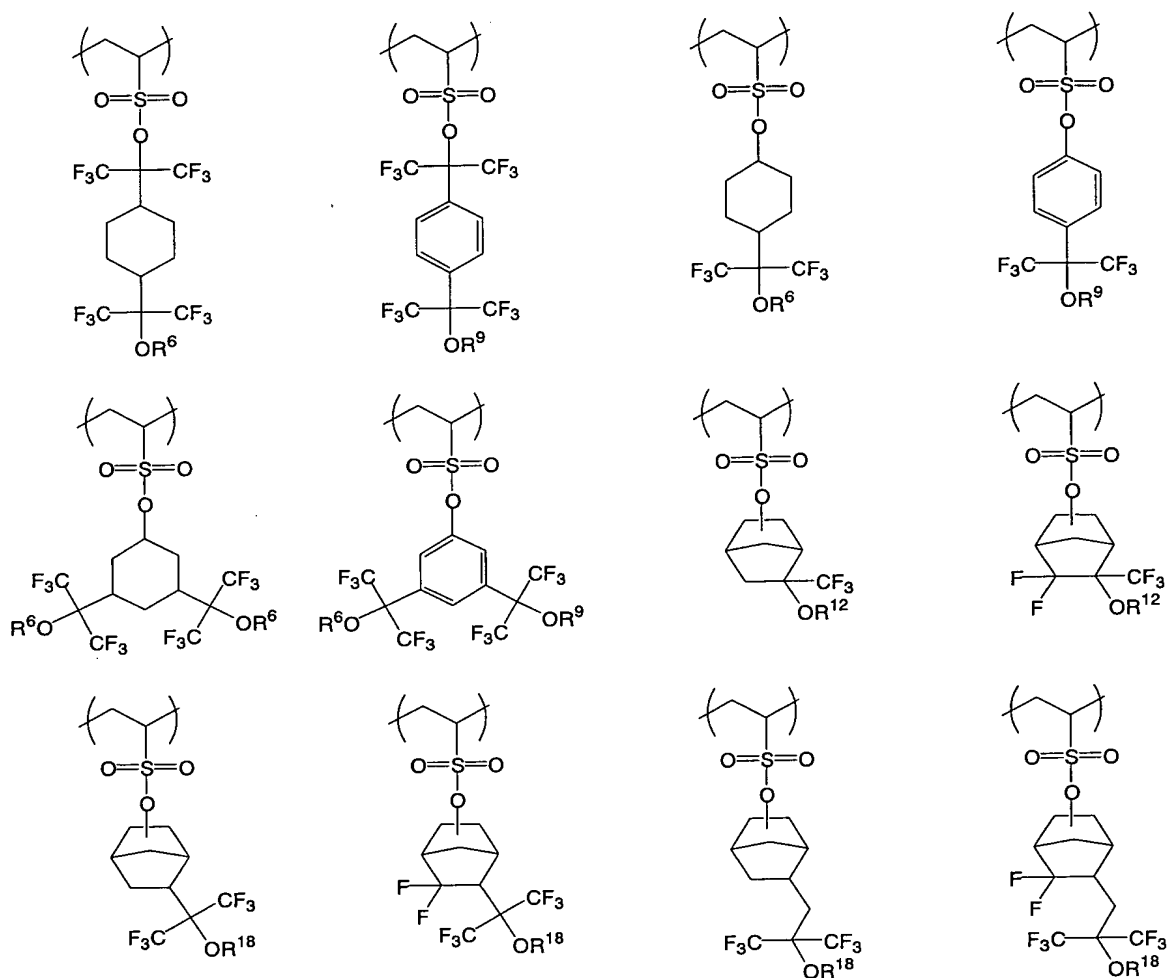


5

[0045]

Illustrative examples of the units of formulae (3a) to (3d) are given below, though not limited thereto.

[0046]
[Formula 31]



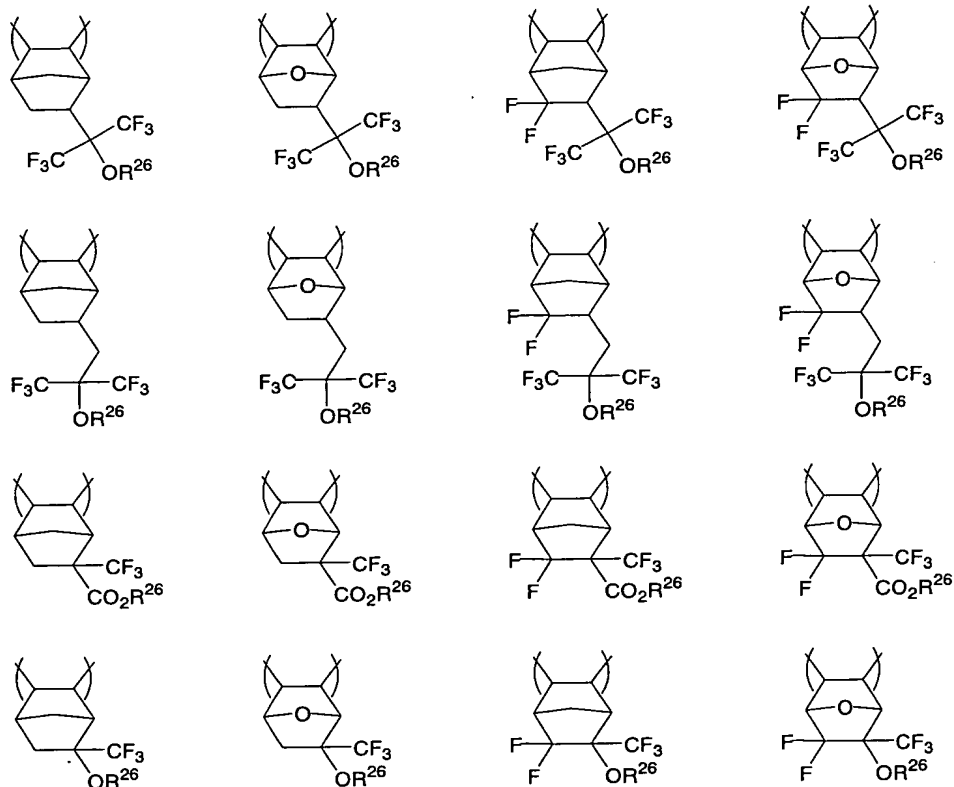
Herein R^6 , R^9 and R^{18} are as defined above.

5 [0047]

Illustrative examples of the units of formulae (4), (4a) and (4b) are given below, though not limited thereto.

[0048]

[Formula 32]



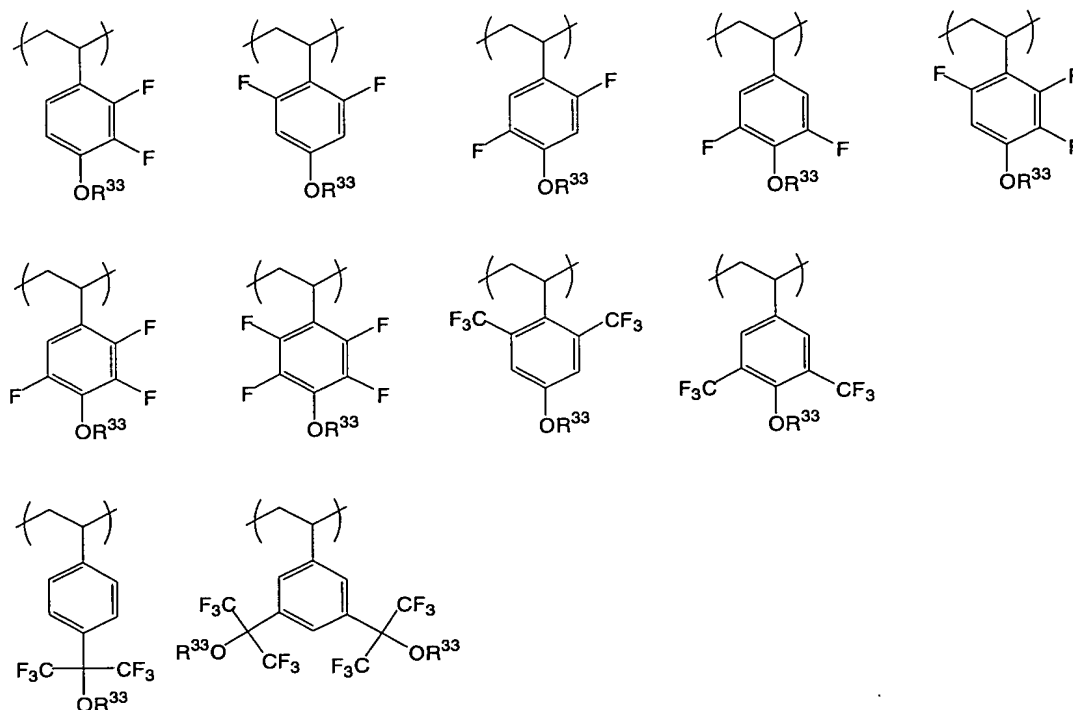
Herein R^{26} is as defined above.

[0049]

5 Illustrative examples of the units of formulae (5), (5a) and (5b) are given below, though not limited thereto.

[0050]

[Formula 33]



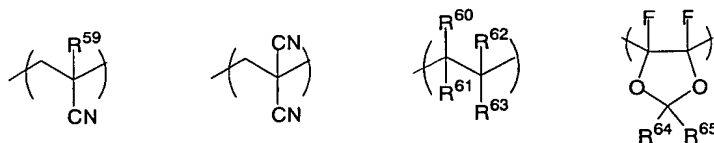
Herein R³³ is as defined above.

5 [0051]

Besides, units as shown below may be incorporated in the inventive polymers for the purpose of improving substrate adhesion and transparency.

[0052]

10 [Formula 34]



Herein, R⁵⁹ to R⁶³ each are hydrogen, fluorine or a fluorinated alkyl group of 1 to 4 carbon atoms, and at least one of R⁶⁰ to R⁶³ contains at least one fluorine atom. R⁶⁴ and R⁶⁵ each are hydrogen, methyl or trifluoromethyl.

15 [0053]

In the inventive polymers wherein U1 represents units of formula (2), U2 represents units of formulae (3a) to

(3f), U3 represents units of formulae (4), (4a) and (4c), U4 represents units of formulae (5), (5a) and (5c), U5 represents units of formula (6), and U6 represents adhesive and transparent units other than the foregoing, and

5 $U1+U2+U3+U4+U5+U6 = 1$, U's are preferably in the range:

$0 < U1 \leq 0.9$, more preferably $0.1 \leq U1 \leq 0.5$,

$0 \leq U2 \leq 0.6$, more preferably $0 \leq U2 \leq 0.4$,

$0 \leq U3 \leq 0.6$, more preferably $0 \leq U3 \leq 0.4$,

$0 \leq U4 \leq 0.6$, more preferably $0 \leq U4 \leq 0.4$,

10 $0 \leq U5 \leq 0.7$, more preferably $0 \leq U5 \leq 0.5$, and

$0 \leq U6 \leq 0.4$, more preferably $0 \leq U6 \leq 0.2$.

[0054]

The polymers of the invention are generally synthesized by dissolving monomers corresponding to the
15 respective units of formulae (2), (3a) to (3f), (4), (4a), (4b), (5), (5a), (5b) and (6) and optionally, an adhesion-improving monomer, a transparency-improving monomer and the like in a solvent, adding a catalyst thereto, and effecting polymerization reaction while heating or cooling
20 the system if necessary. The polymerization reaction depends on the type of initiator or catalyst, trigger means (including light, heat, radiation and plasma), and polymerization conditions (including temperature, pressure, concentration, solvent, and additives). Commonly used for
25 preparation of the polymers of the invention are radical copolymerization of triggering polymerization with initiators such as 2,2'-azobisisobutyronitrile (AIBN) or the like, and ion (anion) polymerization using catalysts such as alkyl lithium. These polymerization steps may be carried
30 out in their conventional manner.

[0055]

The radical polymerization initiator used herein is not critical. Exemplary initiators include azo compounds such as AIBN, 2,2'-azobis(4-methoxy-2,4-dimethylvaleronitrile),
35 2,2'-azobis(2,4-dimethylvaleronitrile), and 2,2'-azobis(2,4,4-trimethylpentane); peroxide compounds such

as tert-butyl peroxyvalate, lauroyl peroxide, benzoyl peroxide and tert-butyl peroxyaurate; water-soluble initiators, for example, persulfate salts such as potassium persulfate; and redox combinations of potassium persulfate or peroxides such as hydrogen peroxide with reducing agents such as sodium sulfite. The amount of the polymerization initiator used is determined as appropriate in accordance with such factors as the identity of initiator and polymerization conditions, although the amount is often in the range of 0.001 to 5% by weight, especially 0.01 to 2% by weight based on the total weight of monomers to be polymerized.

[0056]

For the polymerization reaction, a solvent may be used. The polymerization solvent used herein is preferably one which does not interfere with the polymerization reaction. Typical solvents include ester solvents such as ethyl acetate and n-butyl acetate, ketone solvents such as acetone, methyl ethyl ketone and methyl isobutyl ketone, aliphatic or aromatic hydrocarbon solvents such as toluene, xylene and cyclohexane, alcohol solvents such as isopropyl alcohol and ethylene glycol monomethyl ether, and ether solvents such as diethyl ether, dioxane, and tetrahydrofuran. These solvents may be used alone or in admixture of two or more. Further, any of well-known molecular weight modifiers such as dodecylmercaptan may be used in the polymerization system.

[0057]

The temperature of polymerization reaction varies in accordance with the identity of polymerization initiator and the boiling point of the solvent although it is often preferably in the range of 20 to 200°C, and especially 50 to 140°C. Any desired reactor or vessel may be used for the polymerization reaction.

[0058]

From the solution or dispersion of the polymer thus obtained, the organic solvent or water serving as the

reaction medium is removed by any of well-known techniques. Suitable techniques include, for example, re-precipitation followed by filtration, and heat distillation under vacuum.

[0059]

5 Desirably the polymer has a weight average molecular weight of 1,000 to 500,000, and especially 2,000 to 100,000.

[0060]

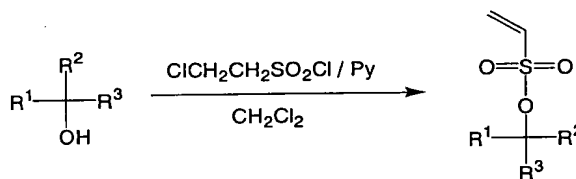
The polymer of the invention can be used as a base resin in resist compositions, specifically chemical
10 amplification type resist compositions, and especially chemical amplification type positive working resist compositions. It is understood that the polymer of the invention may be admixed with another polymer for the purpose of altering the dynamic properties, thermal
15 properties, alkali solubility and other physical properties of polymer film. The type of the other polymer which can be admixed is not critical. Any of polymers known to be useful in resist use may be admixed in any desired proportion.

[0061]

20 In the practice of the invention, the sulfonate compounds can be prepared by the following scheme, although their preparation is not limited thereto.

[0062]

[Formula 35]



25 [0063]

Herein R¹ to R³ are as defined above. The reaction readily takes place under well-known conditions. Preferably, the alcohol reactant and a base such as pyridine are simultaneously added to a solvent such as
30 dichloromethane, and chloroethanesulfonyl chloride is added dropwise under ice cooling. The desired monomer is obtained in this way.

[0064]

As long as the polymer of the invention is used as a base resin, the resist composition of the invention may be prepared using well-known components. In a preferred

embodiment, the chemically amplified positive resist composition is defined as comprising

(A) the above-defined polymer as a base resin,

(B) an organic solvent, and

(C) a photoacid generator.

In the resist composition, there may be further formulated

(D) a basic compound and/or

(E) a dissolution inhibitor.

[0065]

The organic solvent used as component (B) in the invention may be any organic solvent in which the base resin, photoacid generator, and other components are

soluble. Illustrative, non-limiting, examples of the organic solvent include ketones such as cyclohexanone and methyl-2-n-amylketone; alcohols such as 3-methoxybutanol,

3-methyl-3-methoxybutanol, 1-methoxy-2-propanol, and 1-ethoxy-2-propanol; ethers such as propylene glycol monomethyl ether, ethylene glycol monomethyl ether,

propylene glycol monoethyl ether, ethylene glycol monoethyl ether, propylene glycol dimethyl ether, and diethylene glycol dimethyl ether; esters such as propylene glycol monomethyl ether acetate, propylene glycol monoethyl ether acetate, ethyl lactate, ethyl pyruvate, butyl acetate,

methyl 3-methoxypropionate, ethyl 3-ethoxypropionate, tert-butyl acetate, tert-butyl propionate, and propylene glycol mono-tert-butyl ether acetate; and lactones such as

γ -butyrolactone.

[0066]

Also useful are fluorinated organic solvents.

Illustrative, non-limiting examples include 2-fluoroanisole,

3-fluoroanisole, 4-fluoroanisole, 2,3-difluoroanisole,

2,4-difluoroanisole, 2,5-difluoroanisole,

5,8-difluoro-1,4-benzodioxane, 2,3-difluorobenzyl alcohol,
1,3-difluoro-2-propanol, 2',4'-difluoropropiophenone,
2,4-difluorotoluene, trifluoroacetaldehyde ethyl hemiacetal,
trifluoroacetamide, trifluoroethanol,
5 2,2,2-trifluorobutyrate, ethylheptafluoroethanol, ethyl
heptafluorobutylacetate, ethyl hexafluoroglutaryl methyl,
ethyl 3-hydroxy-4,4,4-trifluoroacetoacetate,
ethyl pentafluoropropynylacetate, ethyl perfluorooctanoate,
ethyl 4,4,4-trifluoroacetoacetate,
10 ethyl 4,4,4-trifluorobutyrate,
ethyl 4,4,4-trifluorocrotonate, ethyl trifluoropyruvate,
sec-ethyl trifluoroacetate, fluorocyclohexane,
2,2,3,3,4,4,4-heptafluoro-1-butanol,
1,1,1,2,2,3,3-heptafluoro-7,7-dimethyl-4,6-octanedione,
15 1,1,1,3,5,5,5-heptafluoropentane-2,4-dione,
3,3,4,4,5,5,5-heptafluoro-2-pentanol,
3,3,4,4,5,5,5-heptafluoro-2-pentanone,
isopropyl 4,4,4-trifluoroacetoacetate,
methyl perfluorodecanoate,
20 methyl perfluoro(2-methyl-3-oxahexanoate),
methyl perfluorononanoate, methyl perfluorooctanoate,
methyl 2,3,3,3-tetrafluoropropionate,
methyl trifluoroacetoacetate,
1,1,1,2,2,6,6,6-octafluoro-2,4-hexanedione,
25 2,2,3,3,4,4,5,5-octafluoro-1-pentanol,
1H,1H,2H,2H-perfluoro-1-decanol,
perfluoro-2,5-dimethyl-3,6-dioxane anionic acid methyl
ester, 2H-perfluoro-5-methyl-3,6-dioxanonane,
1H,1H,2H,3H,3H-perfluorononane-1,2-diol,
30 1H,1H,9H-perfluoro-1-nonanol, 1H,1H-perfluorooctanol,
1H,1H,2H,2H-perfluorooctanol,
2H-perfluoro-5,8,11,14-tetramethyl-3,6,9,12,15-pentaoxa-
octadecane,
perfluorotributylamine, perfluorotrihexylamine,
35 perfluoro-2,5,8-trimethyl-3,6,9,12,15-pentaoxaoctadecane,
perfluorotributylamine, perfluorotrihexylamine,

methyl perfluoro-2,5,8-trimethyl-3,6,9-trioxadodecanoate,
perfluorotripentylamine, perfluorotriisopropylamine,
1H,1H,2H,3H,3H-perfluoroundecane-1,2-diol,
trifluorobutanol, 1,1,1-trifluoro-5-methyl-2,4-hexanedione,
5 1,1,1-trifluoro-2-propanol, 3,3,3-trifluoro-1-propanol,
1,1,1-trifluoro-2-propyl acetate,
perfluorobutyltetrahydrofuran, perfluorodecalin,
perfluoro(1,2-dimethylcyclohexane),
perfluoro(1,3-dimethylcyclohexane),
10 propylene glycol trifluoromethyl ether acetate,
propylene glycol methyl ether trifluoromethyl acetate,
butyl trifluoromethylacetate,
methyl 3-trifluoromethoxypropionate, perfluorocyclohexane,
propylene glycol trifluoromethyl ether,
15 butyl trifluoroacetate, and
1,1,1-trifluoro-5,5-dimethyl-2,4-hexanedione.

[0067]

These solvents may be used alone or in combinations of
two or more thereof. Of the above organic solvents,
20 preferred are diethylene glycol dimethyl ether and
1-ethoxy-2-propanol, in which the photoacid generator is
most soluble, and propylene glycol monomethyl ether acetate
which is safe, and mixtures thereof.

[0068]

25 The solvent is preferably used in an amount of 300 to
10,000 parts by weight, more preferably 500 to 5,000 parts
by weight per 100 parts by weight of the base resin.

[0069]

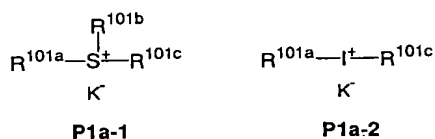
The photoacid generator used as component (C) a
30 compound capable of generating an acid upon exposure to high
energy radiation or electron beams and includes the
following:

- i. onium salts of the formula (Pl-a-1), (Pl-a-2) or (Pl-b),
- ii. diazomethane derivatives of the formula (P2),
- 35 iii. glyoxime derivatives of the formula (P3),
- iv. bissulfone derivatives of the formula (P4),

- v. sulfonic acid esters of N-hydroxyimide compounds of the formula (P5),
- vi. β -ketosulfonic acid derivatives,
- vii. disulfone derivatives,
- 5 viii. nitrobenzylsulfonate derivatives, and
- ix. sulfonate derivatives.

[0070]

[Formula 36]



Herein, R^{101a} , R^{101b} , and R^{101c} independently represent straight,
 10 branched or cyclic alkyl, alkenyl, oxoalkyl or oxoalkenyl
 groups of 1 to 12 carbon atoms, aryl groups of 6 to 20
 carbon atoms, or aralkyl or aryloxoalkyl groups of 7 to 12
 carbon atoms, wherein some or all of the hydrogen atoms may
 be replaced by alkoxy or other groups. Also, R^{101b} and R^{101c} ,
 15 taken together, may form a ring. R^{101b} and R^{101c} each are
 alkylene groups of 1 to 6 carbon atoms when they form a
 ring. K^- is a non-nucleophilic counter ion.

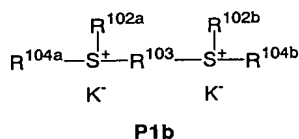
[0071]

R^{101a} , R^{101b} , and R^{101c} may be the same or different and are
 20 illustrated below. Exemplary alkyl groups include methyl,
 ethyl, propyl, isopropyl, n-butyl, sec-butyl, tert-butyl,
 pentyl, hexyl, heptyl, octyl, cyclopentyl, cyclohexyl,
 cycloheptyl, cyclopropylmethyl, 4-methylcyclohexyl,
 cyclohexylmethyl, norbornyl, and adamantyl. Exemplary
 25 alkenyl groups include vinyl, allyl, propenyl, butenyl,
 hexenyl, and cyclohexenyl. Exemplary oxoalkyl groups include
 2-oxocyclopentyl and 2-oxocyclohexyl as well as 2-oxopropyl,
 2-cyclopentyl-2-oxoethyl, 2-cyclohexyl-2-oxoethyl, and
 2-(4-methylcyclohexyl)-2-oxoethyl. Exemplary aryl groups
 30 include phenyl and naphthyl; alkoxyphenyl groups such as
 p-methoxyphenyl, m-methoxyphenyl, o-methoxyphenyl,
 ethoxyphenyl, p-tert-butoxyphenyl, and m-tert-butoxyphenyl;
 alkylphenyl groups such as 2-methylphenyl, 3-methylphenyl,

4-methylphenyl, ethylphenyl, 4-tert-butylphenyl, 4-butylphenyl, and dimethylphenyl; alkylnaphthyl groups such as methylnaphthyl and ethylnaphthyl; alkoxy-naphthyl groups such as methoxynaphthyl and ethoxynaphthyl; dialkylnaphthyl groups such as dimethylnaphthyl and diethylnaphthyl; and dialkoxy-naphthyl groups such as dimethoxynaphthyl and diethoxynaphthyl. Exemplary aralkyl groups include benzyl, phenylethyl, and phenethyl. Exemplary aryloxoalkyl groups are 2-aryl-2-oxoethyl groups such as 2-phenyl-2-oxoethyl, 2-(1-naphthyl)-2-oxoethyl, and 2-(2-naphthyl)-2-oxoethyl. Examples of the non-nucleophilic counter ion represented by K^+ include halide ions such as chloride and bromide ions, fluoroalkylsulfonate ions such as triflate, 1,1,1-trifluoroethanesulfonate, and nonafluorobutanesulfonate, arylsulfonate ions such as tosylate, benzenesulfonate, 4-fluorobenzenesulfonate, and 1,2,3,4,5-pentafluorobenzenesulfonate, and alkylsulfonate ions such as mesylate and butanesulfonate.

[0072]

[Formula 37]



Herein, R^{102a} and R^{102b} independently represent straight, branched or cyclic alkyl groups of 1 to 8 carbon atoms. R^{103} represents a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms. R^{104a} and R^{104b} independently represent 2-oxoalkyl groups of 3 to 7 carbon atoms. K^+ is a non-nucleophilic counter ion.

[0073]

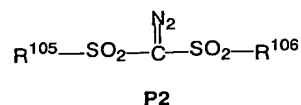
Illustrative of the groups represented by R^{102a} and R^{102b} are methyl, ethyl, propyl, isopropyl, n-butyl, sec-butyl, tert-butyl, pentyl, hexyl, heptyl, octyl, cyclopentyl, cyclohexyl, cyclopropylmethyl, 4-methylcyclohexyl, and cyclohexylmethyl. Illustrative of the groups represented by R^{103} are methylene, ethylene, propylene, butylene, pentylene,

hexylene, heptylene, octylene, nonylene, 1,4-cyclohexylene, 1,2-cyclohexylene, 1,3-cyclopentylene, 1,4-cyclooctylene, and 1,4-cyclohexanedimethylene. Illustrative of the groups represented by R^{104a} and R^{104b} are 2-oxopropyl,

5 2-oxocyclopentyl, 2-oxocyclohexyl, and 2-oxocycloheptyl. Illustrative examples of the counter ion represented by K^+ are the same as exemplified for formulae (Pla-1) and (Pla-2).

[0074]

[Formula 38]



10

Herein, R^{105} and R^{106} independently represent straight, branched or cyclic alkyl or halogenated alkyl groups of 1 to 12 carbon atoms, aryl or halogenated aryl groups of 6 to 20 carbon atoms, or aralkyl groups of 7 to 12 carbon atoms.

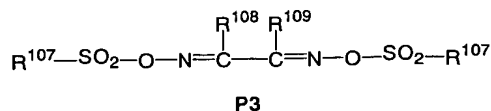
15

[0075]

Of the groups represented by R^{105} and R^{106} , exemplary alkyl groups include methyl, ethyl, propyl, isopropyl, n-butyl, sec-butyl, tert-butyl, pentyl, hexyl, heptyl, octyl, amyl, cyclopentyl, cyclohexyl, cycloheptyl, 20 norbornyl, and adamantyl. Exemplary halogenated alkyl groups include trifluoromethyl, 1,1,1-trifluoroethyl, 1,1,1-trichloroethyl, and nonafluorobutyl. Exemplary aryl groups include phenyl; alkoxyphenyl groups such as p-methoxyphenyl, m-methoxyphenyl, o-methoxyphenyl, 25 ethoxyphenyl, p-tert-butoxyphenyl, and m-tert-butoxyphenyl; and alkylphenyl groups such as 2-methylphenyl, 3-methylphenyl, 4-methylphenyl, ethylphenyl, 4-tert-butylphenyl, 4-butylphenyl, and dimethylphenyl. Exemplary halogenated aryl groups include fluorophenyl, 30 chlorophenyl, and 1,2,3,4,5-pentafluorophenyl. Exemplary aralkyl groups include benzyl and phenethyl.

[0076]

[Formula 39]



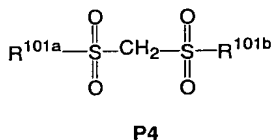
Herein, R^{107} , R^{108} , and R^{109} independently represent straight, branched or cyclic alkyl or halogenated alkyl groups of 1 to 12 carbon atoms, aryl or halogenated aryl groups of 6 to 20 carbon atoms, or aralkyl groups of 7 to 12 carbon atoms. Also, R^{108} and R^{109} , taken together, may form a ring. R^{108} and R^{109} each are straight or branched alkylene groups of 1 to 6 carbon atoms when they form a ring.

[0077]

Illustrative examples of the alkyl, halogenated alkyl, aryl, halogenated aryl, and aralkyl groups represented by R^{107} , R^{108} , and R^{109} are the same as exemplified for R^{105} and R^{106} . Examples of the alkylene groups represented by R^{108} and R^{109} include methylene, ethylene, propylene, butylene, and hexylene.

[0078]

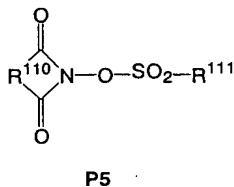
[Formula 40]



Herein, R^{101a} and R^{101b} are as defined above.

[0079]

[Formula 41]



Herein, R^{110} is an arylene group of 6 to 10 carbon atoms, alkylene group of 1 to 6 carbon atoms, or alkenylene group of 2 to 6 carbon atoms wherein some or all of the hydrogen

atoms may be replaced by straight or branched alkyl or alkoxy groups of 1 to 4 carbon atoms, nitro, acetyl, or phenyl groups. R^{111} is a straight, branched or cyclic alkyl group of 1 to 8 carbon atoms, alkenyl, alkoxyalkyl, phenyl or naphthyl group wherein some or all of the hydrogen atoms may be replaced by alkyl or alkoxy groups of 1 to 4 carbon atoms, phenyl groups (which may have substituted thereon an alkyl or alkoxy of 1 to 4 carbon atoms, nitro, or acetyl group), hetero-aromatic groups of 3 to 5 carbon atoms, or chlorine or fluorine atoms.

[0080]

Of the groups represented by R^{110} , exemplary arylene groups include 1,2-phenylene and 1,8-naphthylene; exemplary alkylene groups include methylene, ethylene, trimethylene, tetramethylene, phenylethylene, and norbornane-2,3-diyl; and exemplary alkenylene groups include 1,2-vinylene, 1-phenyl-1,2-vinylene, and 5-norbornene-2,3-diyl. Of the groups represented by R^{111} , exemplary alkyl groups are as exemplified for R^{101a} to R^{101c} ; exemplary alkenyl groups include vinyl, 1-propenyl, allyl, 1-butenyl, 3-butenyl, isoprenyl, 1-pentenyl, 3-pentenyl, 4-pentenyl, dimethylallyl, 1-hexenyl, 3-hexenyl, 5-hexenyl, 1-heptenyl, 3-heptenyl, 6-heptenyl, and 7-octenyl; and exemplary alkoxyalkyl groups include methoxymethyl, ethoxymethyl, propoxymethyl, butoxymethyl, pentyloxymethyl, hexyloxymethyl, heptyloxymethyl, methoxyethyl, ethoxyethyl, propoxyethyl, butoxyethyl, pentyloxyethyl, hexyloxyethyl, methoxypropyl, ethoxypropyl, propoxypropyl, butoxypropyl, methoxybutyl, ethoxybutyl, propoxybutyl, methoxypentyl, ethoxypentyl, methoxyhexyl, and methoxyheptyl.

[0081]

Of the substituents on these groups, the alkyl groups of 1 to 4 carbon atoms include methyl, ethyl, propyl, isopropyl, n-butyl, isobutyl and tert-butyl; the alkoxy groups of 1 to 4 carbon atoms include methoxy, ethoxy, propoxy, isopropoxy, n-butoxy, isobutoxy, and tert-butoxy; the phenyl groups which may have substituted thereon an

alkyl or alkoxy of 1 to 4 carbon atoms, nitro, or acetyl group include phenyl, tolyl, p-tert-butoxyphenyl, p-acetylphenyl and p-nitrophenyl; the hetero-aromatic groups of 3 to 5 carbon atoms include pyridyl and furyl.

5 [0082]

Illustrative examples of the photoacid generator include:

onium salts such as
diphenyliodonium trifluoromethanesulfonate,
10 (p-tert-butoxyphenyl)phenyliodonium trifluoromethanesulfonate,
diphenyliodonium p-toluenesulfonate,
(p-tert-butoxyphenyl)phenyliodonium p-toluenesulfonate,
triphenylsulfonium trifluoromethanesulfonate,
(p-tert-butoxyphenyl)diphenylsulfonium trifluoromethane-
15 sulfonate,
bis(p-tert-butoxyphenyl)phenylsulfonium trifluoromethane-
sulfonate,
tris(p-tert-butoxyphenyl)sulfonium
trifluoromethanesulfonate,
20 triphenylsulfonium p-toluenesulfonate,
(p-tert-butoxyphenyl)diphenylsulfonium p-toluenesulfonate,
bis(p-tert-butoxyphenyl)phenylsulfonium p-toluenesulfonate,
tris(p-tert-butoxyphenyl)sulfonium p-toluenesulfonate,
triphenylsulfonium nonafluorobutanesulfonate,
25 triphenylsulfonium butanesulfonate,
trimethylsulfonium trifluoromethanesulfonate,
trimethylsulfonium p-toluenesulfonate,
cyclohexylmethyl(2-oxocyclohexyl)sulfonium trifluoromethane-
sulfonate,
30 cyclohexylmethyl(2-oxocyclohexyl)sulfonium p-toluenesulfonate,
dimethylphenylsulfonium trifluoromethanesulfonate,
dimethylphenylsulfonium p-toluenesulfonate,
dicyclohexylphenylsulfonium trifluoromethanesulfonate,
dicyclohexylphenylsulfonium p-toluenesulfonate,
35 trinaphthylsulfonium trifluoromethanesulfonate,
cyclohexylmethyl(2-oxocyclohexyl)sulfonium trifluoromethane-
sulfonate,

(2-norbornyl)methyl(2-oxocyclohexyl)sulfonium trifluoromethanesulfonate,
ethylenebis[methyl(2-oxocyclopentyl)sulfonium trifluoromethanesulfonate], and
5 1,2'-naphthylcarbonylmethyltetrahydrothiophenium triflate;
diazomethane derivatives such as
bis(benzenesulfonyl)diazomethane,
bis(p-toluenesulfonyl)diazomethane,
bis(xylenesulfonyl)diazomethane,
10 bis(cyclohexylsulfonyl)diazomethane,
bis(cyclopentylsulfonyl)diazomethane,
bis(n-butylsulfonyl)diazomethane,
bis(isobutylsulfonyl)diazomethane,
bis(sec-butylsulfonyl)diazomethane,
15 bis(n-propylsulfonyl)diazomethane,
bis(isopropylsulfonyl)diazomethane,
bis(tert-butylsulfonyl)diazomethane,
bis(n-amylsulfonyl)diazomethane,
bis(isoamylsulfonyl)diazomethane,
20 bis(sec-amylsulfonyl)diazomethane,
bis(tert-amylsulfonyl)diazomethane,
1-cyclohexylsulfonyl-1-(tert-butylsulfonyl)diazomethane,
1-cyclohexylsulfonyl-1-(tert-amylsulfonyl)diazomethane, and
1-tert-amylsulfonyl-1-(tert-butylsulfonyl)diazomethane;
25 glyoxime derivatives such as
bis-O-(p-toluenesulfonyl)- α -dimethylglyoxime,
bis-O-(p-toluenesulfonyl)- α -diphenylglyoxime,
bis-O-(p-toluenesulfonyl)- α -dicyclohexylglyoxime,
bis-O-(p-toluenesulfonyl)-2,3-pentanedione-glyoxime,
30 bis-O-(p-toluenesulfonyl)-2-methyl-3,4-pentanedione-glyoxime,
bis-O-(n-butanedisulfonyl)- α -dimethylglyoxime,
bis-O-(n-butanedisulfonyl)- α -diphenylglyoxime,
bis-O-(n-butanedisulfonyl)- α -dicyclohexylglyoxime,
bis-O-(n-butanedisulfonyl)-2,3-pentanedione-glyoxime,
35 bis-O-(n-butanedisulfonyl)-2-methyl-3,4-pentanedione-glyoxime,

- bis-O-(methanesulfonyl)- α -dimethylglyoxime,
bis-O-(trifluoromethanesulfonyl)- α -dimethylglyoxime,
bis-O-(1,1,1-trifluoroethanesulfonyl)- α -dimethylglyoxime,
bis-O-(tert-butanesulfonyl)- α -dimethylglyoxime,
5 bis-O-(perfluorooctanesulfonyl)- α -dimethylglyoxime,
bis-O-(cyclohexanesulfonyl)- α -dimethylglyoxime,
bis-O-(benzenesulfonyl)- α -dimethylglyoxime,
bis-O-(p-fluorobenzenesulfonyl)- α -dimethylglyoxime,
bis-O-(p-tert-butylbenzenesulfonyl)- α -dimethylglyoxime,
10 bis-O-(xylenesulfonyl)- α -dimethylglyoxime, and
bis-O-(camphorsulfonyl)- α -dimethylglyoxime;
bissulfone derivatives such as
bisenaphthylsulfonylmethane,
bistrifluoromethylsulfonylmethane, bismethylsulfonylmethane,
15 bisethylsulfonylmethane,
bispropylsulfonylmethane, bisisopropylsulfonylmethane,
bis-p-toluenesulfonylmethane, and bisbenzenesulfonylmethane;
 β -ketosulfone derivatives such as
2-cyclohexylcarbonyl-2-(p-toluenesulfonyl)propane and
20 2-isopropylcarbonyl-2-(p-toluenesulfonyl)propane;
nitrobenzyl sulfonate derivatives such as
2,6-dinitrobenzyl p-toluenesulfonate and
2,4-dinitrobenzyl p-toluenesulfonate;
sulfonic acid ester derivatives such as
25 1,2,3-tris(methanesulfonyloxy)benzene,
1,2,3-tris(trifluoromethanesulfonyloxy)benzene, and
1,2,3-tris(p-toluenesulfonyloxy)benzene; and
sulfonic acid esters of N-hydroxyimides such as
N-hydroxysuccinimide methanesulfonate,
30 N-hydroxysuccinimide trifluoromethanesulfonate,
N-hydroxysuccinimide ethanesulfonate,
N-hydroxysuccinimide 1-propanesulfonate,
N-hydroxysuccinimide 2-propanesulfonate,
N-hydroxysuccinimide 1-pentanesulfonate,

- N-hydroxysuccinimide 1-octanesulfonate,
N-hydroxysuccinimide p-toluenesulfonate,
N-hydroxysuccinimide p-methoxybenzenesulfonate,
N-hydroxysuccinimide 2-chloroethanesulfonate,
5 N-hydroxysuccinimide benzenesulfonate,
N-hydroxysuccinimide 2,4,6-trimethylbenzenesulfonate,
N-hydroxysuccinimide 1-naphthalenesulfonate,
N-hydroxysuccinimide 2-naphthalenesulfonate,
N-hydroxy-2-phenylsuccinimide methanesulfonate,
10 N-hydroxymaleimide methanesulfonate,
N-hydroxymaleimide ethanesulfonate,
N-hydroxy-2-phenylmaleimide methanesulfonate,
N-hydroxyglutarimide methanesulfonate,
N-hydroxyglutarimide benzenesulfonate,
15 N-hydroxyphthalimide methanesulfonate,
N-hydroxyphthalimide benzenesulfonate,
N-hydroxyphthalimide trifluoromethanesulfonate,
N-hydroxyphthalimide p-toluenesulfonate,
N-hydroxynaphthalimide methanesulfonate,
20 N-hydroxynaphthalimide benzenesulfonate,
N-hydroxy-5-norbornene-2,3-dicarboxyimide methanesulfonate,
N-hydroxy-5-norbornene-2,3-dicarboxyimide trifluoromethane-
sulfonate, and
N-hydroxy-5-norbornene-2,3-dicarboxyimide p-toluenesulfonate.
- 25 Preferred among these photoacid generators are onium
salts such as triphenylsulfonium trifluoromethanesulfonate,
(p-tert-butoxyphenyl)diphenylsulfonium trifluoromethane-
sulfonate,
tris(p-tert-butoxyphenyl)sulfonium trifluoromethanesulfonate,
30 triphenylsulfonium p-toluenesulfonate,
(p-tert-butoxyphenyl)diphenylsulfonium p-toluenesulfonate,
tris(p-tert-butoxyphenyl)sulfonium p-toluenesulfonate,
trinaphthylsulfonium trifluoromethanesulfonate,
cyclohexylmethyl(2-oxocyclohexyl)sulfonium trifluoromethane-
35 sulfonate,
(2-norbornyl)methyl(2-oxocyclohexyl)sulfonium trifluoro-
methanesulfonate, and

1,2'-naphthylcarbonylmethyltetrahydrothiophenium triflate;
diazomethane derivatives such as
bis(benzenesulfonyl)diazomethane,
bis(p-toluenesulfonyl)diazomethane,
5 bis(cyclohexylsulfonyl)diazomethane,
bis(n-butylsulfonyl)diazomethane,
bis(isobutylsulfonyl)diazomethane,
bis(sec-butylsulfonyl)diazomethane,
bis(n-propylsulfonyl)diazomethane,
10 bis(isopropylsulfonyl)diazomethane, and
bis(tert-butylsulfonyl)diazomethane;
glyoxime derivatives such as
bis-O-(p-toluenesulfonyl)- α -dimethylglyoxime and
bis-O-(n-butan sulfonyl)- α -dimethylglyoxime;
15 bissulfone derivatives such as
bisnaphthylsulfonylmethane; and sulfonic acid esters of
N-hydroxyimide compounds such as
N-hydroxysuccinimide methanesulfonate,
N-hydroxysuccinimide trifluoromethanesulfonate,
20 N-hydroxysuccinimide 1-propanesulfonate,
N-hydroxysuccinimide 2-propanesulfonate,
N-hydroxysuccinimide 1-pentanesulfonate,
N-hydroxysuccinimide p-toluenesulfonate,
N-hydroxynaphthalimide methanesulfonate, and
25 N-hydroxynaphthalimide benzenesulfonate.

[0083]

These photoacid generators may be used singly or in combinations of two or more thereof. Onium salts are effective for improving rectangularity, while diazomethane
30 derivatives and glyoxime derivatives are effective for reducing standing waves. The combination of an onium salt with a diazomethane or a glyoxime derivative allows for fine adjustment of the profile.

[0084]

35 The photoacid generator is added in an amount of 0.1 to 50 parts, and especially 0.5 to 40 parts by weight, per 100 parts by weight of the base resin (all parts are by

weight, hereinafter). Less than 0.1 part of the photoacid generator may generate a less amount of acid upon exposure, sometimes leading to a poor sensitivity and resolution whereas more than 50 parts of the photoacid generator may
5 adversely affect transmittance and resolution.

[0085]

The basic compound used as component (D) is preferably a compound capable of suppressing the rate of diffusion when the acid generated by the photoacid generator diffuses
10 within the resist film. The inclusion of this type of basic compound holds down the rate of acid diffusion within the resist film, resulting in better resolution. In addition, it suppresses changes in sensitivity following exposure, thus reducing substrate and environment dependence, as well
15 as improving the exposure latitude and the pattern profile.

[0086]

Examples of suitable basic compounds include primary, secondary, and tertiary aliphatic amines, mixed amines, aromatic amines, heterocyclic amines, carboxyl group-bearing
20 nitrogenous compounds, sulfonyl group-bearing nitrogenous compounds, hydroxyl group-bearing nitrogenous compounds, hydroxyphenyl group-bearing nitrogenous compounds, alcoholic nitrogenous compounds, amide derivatives, and imide derivatives.

25 [0087]

Examples of suitable primary aliphatic amines include ammonia, methylamine, ethylamine, n-propylamine, isopropylamine, n-butylamine, iso-butylamine, sec-butylamine, tert-butylamine, pentylamine,
30 tert-amylamine, cyclopentylamine, hexylamine, cyclohexylamine, heptylamine, octylamine, nonylamine, decylamine, dodecylamine, cetylamine, methylenediamine, ethylenediamine, and tetraethylenepentamine. Examples of suitable secondary aliphatic amines include dimethylamine,
35 diethylamine, di-n-propylamine, di-iso-propylamine, di-n-butylamine, di-iso-butylamine, di-sec-butylamine, dipentylamine, dicyclopentylamine, dihexylamine,

dicyclohexylamine, diheptylamine, dioctylamine, dinonylamine, didecylamine, didodecylamine, dicetylamine, N,N-dimethylmethylenediamine, N,N-dimethylethylenediamine, and N,N-dimethyltetraethylenepentamine. Examples of
5 suitable tertiary aliphatic amines include trimethylamine, triethylamine, tri-n-propylamine, tri-iso-propylamine, tri-n-butylamine, tri-iso-butylamine, tri-sec-butylamine, tripentylamine, tricyclopentylamine, trihexylamine, tricyclohexylamine, triheptylamine, trioctylamine,
10 trinonylamine, tridecylamine, tridodecylamine, tricetylamine, N,N,N',N'-tetramethylmethylenediamine, N,N,N',N'-tetramethylethylenediamine, and N,N,N',N'-tetramethyltetraethylenepentamine.

[0088]

15 Examples of suitable mixed amines include dimethylethylamine, methylethylpropylamine, benzylamine, phenethylamine, and benzyldimethylamine. Examples of suitable aromatic amines include aniline derivatives (e.g., aniline, N-methylaniline, N-ethylaniline, N-propylaniline,
20 N,N-dimethylaniline, 2-methylaniline, 3-methylaniline, 4-methylaniline, ethylaniline, propylaniline, trimethylaniline, 2-nitroaniline, 3-nitroaniline, 4-nitroaniline, 2,4-dinitroaniline, 2,6-dinitroaniline, 3,5-dinitroaniline, and N,N-dimethyltoluidine),
25 diphenyl(p-tolyl)amine, methyldiphenylamine, triphenylamine, phenylenediamine, naphthylamine, and diaminonaphthalene. Examples of suitable heterocyclic amines include pyrrole derivatives (e.g., pyrrole, 2H-pyrrole, 1-methylpyrrole, 2,4-dimethylpyrrole, 2,5-dimethylpyrrole, and
30 N-methylpyrrole), oxazole derivatives (e.g., oxazole and isooxazole), thiazole derivatives (e.g., thiazole and isothiazole), imidazole derivatives (e.g., imidazole, 4-methylimidazole, and 4-methyl-2-phenylimidazole), pyrazole derivatives, furazan derivatives, pyrroline derivatives
35 (e.g., pyrroline and 2-methyl-1-pyrroline), pyrrolidine derivatives (e.g., pyrrolidine, N-methylpyrrolidine, pyrrolidinone, and N-methylpyrrolidone), imidazoline

derivatives, imidazolidine derivatives, pyridine derivatives
(e.g., pyridine, methylpyridine, ethylpyridine,
propylpyridine, butylpyridine, 4-(1-butylpentyl)pyridine,
dimethylpyridine, trimethylpyridine, triethylpyridine,
5 phenylpyridine, 3-methyl-2-phenylpyridine,
4-tert-butylpyridine, diphenylpyridine, benzylpyridine,
methoxypyridine, butoxypyridine, dimethoxypyridine,
1-methyl-2-pyridone, 4-pyrrolidinopyridine,
1-methyl-4-phenylpyridine, 2-(1-ethylpropyl)pyridine,
10 aminopyridine, and dimethylaminopyridine), pyridazine
derivatives, pyrimidine derivatives, pyrazine derivatives,
pyrazoline derivatives, pyrazolidine derivatives, piperidine
derivatives, piperazine derivatives, morpholine derivatives,
indole derivatives, isoindole derivatives, 1H-indazole
15 derivatives, indoline derivatives, quinoline derivatives
(e.g., quinoline and 3-quinolinecarbonitrile), isoquinoline
derivatives, cinnoline derivatives, quinazoline derivatives,
quinoxaline derivatives, phthalazine derivatives, purine
derivatives, pteridine derivatives, carbazole derivatives,
20 phenanthridine derivatives, acridine derivatives, phenazine
derivatives, 1,10-phenanthroline derivatives, adenine
derivatives, adenosine derivatives, guanine derivatives,
guanosine derivatives, uracil derivatives, and uridine
derivatives.

25 [0089]

Examples of suitable carboxyl group-bearing
nitrogenous compounds include aminobenzoic acid,
indolecarboxylic acid, and amino acid derivatives (e.g.,
nicotinic acid, alanine, arginine, aspartic acid, glutamic
30 acid, glycine, histidine, isoleucine, glycylleucine,
leucine, methionine, phenylalanine, threonine, lysine,
3-aminopyrazine-2-carboxylic acid, and methoxyalanine).

Examples of suitable sulfonyl group-bearing
nitrogenous compounds include 3-pyridinesulfonic acid and
35 pyridinium p-toluenesulfonate.

Examples of suitable hydroxyl group-bearing
nitrogenous compounds, hydroxyphenyl group-bearing

nitrogenous compounds, and alcoholic nitrogenous compounds include 2-hydroxypyridine, aminocresol, 2,4-quinolinediol, 3-indolemethanol hydrate, monoethanolamine, diethanolamine, triethanolamine, N-ethyldiethanolamine, 5 N,N-diethylethanolamine, triisopropanolamine, 2,2'-iminodiethanol, 2-aminoethanol, 3-amino-1-propanol, 4-amino-1-butanol, 4-(2-hydroxyethyl)morpholine, 2-(2-hydroxyethyl)pyridine, 1-(2-hydroxyethyl)piperazine, 1-[2-(2-hydroxyethoxy)ethyl]piperazine, piperidine ethanol, 10 1-(2-hydroxyethyl)pyrrolidine, 1-(2-hydroxyethyl)-2-pyrrolidinone, 3-piperidino-1,2-propanediol, 3-pyrrolidino-1,2-propanediol, 8-hydroxyjulolidine, 3-quinuclidinol, 3-tropanol, 1-methyl-2-pyrrolidine ethanol, 1-aziridine ethanol, 15 N-(2-hydroxyethyl)phthalimide, and N-(2-hydroxyethyl)isonicotinamide.

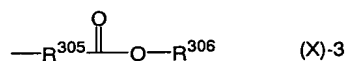
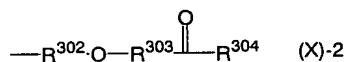
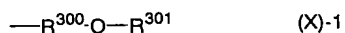
Examples of suitable amide derivatives include formamide, N-methylformamide, N,N-dimethylformamide, acetamide, N-methylacetamide, N,N-dimethylacetamide, 20 propionamide, and benzamide. Suitable imide derivatives include phthalimide, succinimide, and maleimide.

[0090]

In addition, basic compounds of the following general formula (B)-1 may also be included alone or in admixture.

25 [0091]

[Formula 42]



[0092]

In the formulas, n is 1, 2 or 3. The side chain X may be the same or different and is represented by the formula (X)-1 to (X)-3. The side chain Y may be the same or
5 different and stands for hydrogen or a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain an ether or hydroxyl group. Two or three X's may bond together to form a ring.

[0093]

10 In the formulas, R^{300} , R^{302} and R^{305} are independently straight or branched alkylene groups of 1 to 4 carbon atoms; R^{301} and R^{304} are independently hydrogen, straight, branched or cyclic alkyl groups of 1 to 20 carbon atoms, which may contain at least one hydroxyl group, ether, ester or lactone
15 ring; and R^{303} is a single bond or a straight or branched alkylene group of 1 to 4 carbon atoms; and R^{306} is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms, which may contain at least one hydroxyl group, ether, ester or lactone ring.

20 [0094]

Illustrative, non-limiting examples of the compounds of formula (B)-1 include tris(2-methoxymethoxyethyl)amine, tris{2-(2-methoxyethoxy)ethyl}amine, tris{2-(2-methoxyethoxymethoxy)ethyl}amine,
25 tris{2-(1-methoxyethoxy)ethyl}amine, tris{2-(1-ethoxyethoxy)ethyl}amine, tris{2-(1-ethoxypropoxy)ethyl}amine, tris[2-{2-(2-hydroxyethoxy)ethoxy}ethyl]amine, 4,7,13,16,21,24-hexaoxa-1,10-diazabicyclo[8.8.8]hexacosane,
30 4,7,13,18-tetraoxa-1,10-diazabicyclo[8.5.5]eicosane, 1,4,10,13-tetraoxa-7,16-diazabicyclooctadecane, 1-aza-12-crown-4, 1-aza-15-crown-5, 1-aza-18-crown-6, tris(2-formyloxyethyl)amine, tris(2-acetoxyethyl)amine, tris(2-propionyloxyethyl)amine, tris(2-butyryloxyethyl)amine,
35 tris(2-isobutyryloxyethyl)amine, tris(2-valeryloxyethyl)amine, tris(2-pivaloyloxyethyl)amine, N,N-bis(2-acetoxyethyl)-2-(acetoxycetoxy)ethylamine,

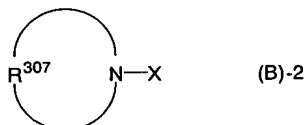
tris(2-methoxycarbonyloxyethyl)amine,
tris(2-tert-butoxycarbonyloxyethyl)amine,
tris[2-(2-oxopropoxy)ethyl]amine,
tris[2-(methoxycarbonylmethyl)oxyethyl]amine,
5 tris[2-(tert-butoxycarbonylmethyloxy)ethyl]amine,
tris[2-(cyclohexyloxycarbonylmethyloxy)ethyl]amine,
tris(2-methoxycarbonylethyl)amine,
tris(2-ethoxycarbonylethyl)amine,
N,N-bis(2-hydroxyethyl)-2-(methoxycarbonyl)ethylamine,
10 N,N-bis(2-acetoxyethyl)-2-(methoxycarbonyl)ethylamine,
N,N-bis(2-hydroxyethyl)-2-(ethoxycarbonyl)ethylamine,
N,N-bis(2-acetoxyethyl)-2-(ethoxycarbonyl)ethylamine,
N,N-bis(2-hydroxyethyl)-2-(2-methoxyethoxycarbonyl)ethylamine,
N,N-bis(2-acetoxyethyl)-2-(2-methoxyethoxycarbonyl)ethylamine,
15 N,N-bis(2-hydroxyethyl)-2-(2-hydroxyethoxycarbonyl)ethylamine,
N,N-bis(2-acetoxyethyl)-2-(2-acetoxyethoxycarbonyl)ethylamine,
N,N-bis(2-hydroxyethyl)-2-[(methoxycarbonyl)methoxycarbonyl]-
ethylamine,
N,N-bis(2-acetoxyethyl)-2-[(methoxycarbonyl)methoxycarbonyl]-
20 ethylamine,
N,N-bis(2-hydroxyethyl)-2-(2-oxopropoxycarbonyl)ethylamine,
N,N-bis(2-acetoxyethyl)-2-(2-oxopropoxycarbonyl)ethylamine,
N,N-bis(2-hydroxyethyl)-2-(tetrahydrofurfuryloxycarbonyl)-
ethylamine,
25 N,N-bis(2-acetoxyethyl)-2-(tetrahydrofurfuryloxycarbonyl)-
ethylamine,
N,N-bis(2-hydroxyethyl)-2-[(2-oxotetrahydrofuran-3-yl)oxy-
carbonyl]ethylamine,
N,N-bis(2-acetoxyethyl)-2-[(2-oxotetrahydrofuran-3-yl)oxy-
30 carbonyl]ethylamine,
N,N-bis(2-hydroxyethyl)-2-(4-hydroxybutoxycarbonyl)ethylamine,
N,N-bis(2-formyloxyethyl)-2-(4-formyloxybutoxycarbonyl)-
ethylamine,
N,N-bis(2-formyloxyethyl)-2-(2-formyloxyethoxycarbonyl)-
35 ethylamine,
N,N-bis(2-methoxyethyl)-2-(methoxycarbonyl)ethylamine,
N-(2-hydroxyethyl)-bis[2-(methoxycarbonyl)ethyl]amine,

N-(2-acetoxyethyl)-bis[2-(methoxycarbonyl)ethyl]amine,
 N-(2-hydroxyethyl)-bis[2-(ethoxycarbonyl)ethyl]amine,
 N-(2-acetoxyethyl)-bis[2-(ethoxycarbonyl)ethyl]amine,
 N-(3-hydroxy-1-propyl)-bis[2-(methoxycarbonyl)ethyl]amine,
 5 N-(3-acetoxy-1-propyl)-bis[2-(methoxycarbonyl)ethyl]amine,
 N-(2-methoxyethyl)-bis[2-(methoxycarbonyl)ethyl]amine,
 N-butyl-bis[2-(methoxycarbonyl)ethyl]amine,
 N-butyl-bis[2-(2-methoxyethoxycarbonyl)ethyl]amine,
 N-methyl-bis(2-acetoxyethyl)amine,
 10 N-ethyl-bis(2-acetoxyethyl)amine,
 N-methyl-bis(2-pivaloyloxyethyl)amine,
 N-ethyl-bis[2-(methoxycarbonyloxy)ethyl]amine,
 N-ethyl-bis[2-(tert-butoxycarbonyloxy)ethyl]amine,
 tris(methoxycarbonylmethyl)amine,
 15 tris(ethoxycarbonylmethyl)amine,
 N-butyl-bis(methoxycarbonylmethyl)amine,
 N-hexyl-bis(methoxycarbonylmethyl)amine, and
 β -(diethylamino)- δ -valerolactone.

Also useful are one or more of cyclic
 20 structure-bearing basic compounds having the following
 general formula (B)-2.

[0095]

[Formula 43]



Herein X is as defined above, and R^{307} is a straight or
 25 branched alkylene group of 2 to 20 carbon atoms which may
 contain one or more carbonyl, ether, ester or sulfide
 groups.

[0096]

Illustrative examples of the cyclic structure-bearing
 30 basic compounds having formula (B)-2 include

1-[2-(methoxymethoxy)ethyl]pyrrolidine,
 1-[2-(methoxymethoxy)ethyl]piperidine,
 4-[2-(methoxymethoxy)ethyl]morpholine,

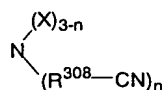
1-[2-[(2-methoxyethoxy)methoxy]ethyl]pyrrolidine,
1-[2-[(2-methoxyethoxy)methoxy]ethyl]piperidine,
4-[2-[(2-methoxyethoxy)methoxy]ethyl]morpholine,
2-(1-pyrrolidinyl)ethyl acetate, 2-piperidinoethyl acetate,
5 2-morpholinoethyl acetate, 2-(1-pyrrolidinyl)ethyl formate,
2-piperidinoethyl propionate,
2-morpholinoethyl acetoxyacetate,
2-(1-pyrrolidinyl)ethyl methoxyacetate,
4-[2-(methoxycarbonyloxy)ethyl]morpholine,
10 1-[2-(t-butoxycarbonyloxy)ethyl]piperidine,
4-[2-(2-methoxyethoxycarbonyloxy)ethyl]morpholine,
methyl 3-(1-pyrrolidinyl)propionate,
methyl 3-piperidinopropionate,
methyl 3-morpholinopropionate,
15 methyl 3-(thiomorpholino)propionate,
methyl 2-methyl-3-(1-pyrrolidinyl)propionate,
ethyl 3-morpholinopropionate,
methoxycarbonylmethyl 3-piperidinopropionate,
2-hydroxyethyl 3-(1-pyrrolidinyl)propionate,
20 2-acetoxyethyl 3-morpholinopropionate,
2-oxotetrahydrofuran-3-yl 3-(1-pyrrolidinyl)propionate,
tetrahydrofurfuryl 3-morpholinopropionate,
glycidyl 3-piperidinopropionate,
2-methoxyethyl 3-morpholinopropionate,
25 2-(2-methoxyethoxy)ethyl 3-(1-pyrrolidinyl)propionate,
butyl 3-morpholinopropionate,
cyclohexyl 3-piperidinopropionate,
 α -(1-pyrrolidinyl)methyl- γ -butyrolactone,
 β -piperidino- γ -butyrolactone, β -morpholino- δ -valerolactone,
30 methyl 1-pyrrolidinylacetate, methyl piperidinoacetate,
methyl morpholinoacetate, methyl thiomorpholinoacetate,
ethyl 1-pyrrolidinylacetate, and
2-methoxyethyl morpholinoacetate.

[0097]

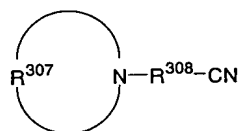
35 Also, one or more of cyano-bearing basic compounds
having the following general formulae (B)-3 to (B)-6 may be
blended.

[0098]

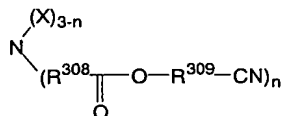
[Formula 44]



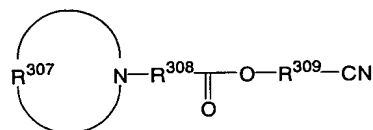
(B)-3



(B)-4



(B)-5



(B)-6

Herein, X, R³⁰⁷ and n are as defined above, and R³⁰⁸ and R³⁰⁹ each are independently a straight or branched alkylene group of 1 to 4 carbon atoms.

[0099]

Illustrative examples of the cyano-bearing basic compounds include 3-(diethylamino)propiononitrile,

- 10 N,N-bis(2-hydroxyethyl)-3-aminopropiononitrile,
N,N-bis(2-acetoxyethyl)-3-aminopropiononitrile,
N,N-bis(2-formyloxyethyl)-3-aminopropiononitrile,
N,N-bis(2-methoxyethyl)-3-aminopropiononitrile,
N,N-bis[2-(methoxymethoxy)ethyl]-3-aminopropiononitrile,
- 15 methyl N-(2-cyanoethyl)-N-(2-methoxyethyl)-3-aminopropionate,
methyl N-(2-cyanoethyl)-N-(2-hydroxyethyl)-3-aminopropionate,
methyl N-(2-acetoxyethyl)-N-(2-cyanoethyl)-3-aminopropionate,
N-(2-cyanoethyl)-N-ethyl-3-aminopropiononitrile,
N-(2-cyanoethyl)-N-(2-hydroxyethyl)-3-aminopropiononitrile,
- 20 N-(2-acetoxyethyl)-N-(2-cyanoethyl)-3-aminopropiononitrile,
N-(2-cyanoethyl)-N-(2-formyloxyethyl)-3-aminopropiononitrile,
N-(2-cyanoethyl)-N-(2-methoxyethyl)-3-aminopropiononitrile,
N-(2-cyanoethyl)-N-[2-(methoxymethoxy)ethyl]-3-aminopropiononitrile,
- 25 N-(2-cyanoethyl)-N-(3-hydroxy-1-propyl)-3-aminopropiononitrile,
N-(3-acetoxy-1-propyl)-N-(2-cyanoethyl)-3-aminopropiononitrile,

N-(2-cyanoethyl)-N-(3-formyloxy-1-propyl)-3-aminopropiononitrile,
N-(2-cyanoethyl)-N-tetrahydrofurfuryl-3-aminopropiononitrile,
N,N-bis(2-cyanoethyl)-3-aminopropiononitrile,
5 diethylaminoacetoneitrile,
N,N-bis(2-hydroxyethyl)aminoacetoneitrile,
N,N-bis(2-acetoxyethyl)aminoacetoneitrile,
N,N-bis(2-formyloxyethyl)aminoacetoneitrile,
N,N-bis(2-methoxyethyl)aminoacetoneitrile,
10 N,N-bis[2-(methoxymethoxy)ethyl]aminoacetoneitrile,
methyl N-cyanomethyl-N-(2-methoxyethyl)-3-aminopropionate,
methyl N-cyanomethyl-N-(2-hydroxyethyl)-3-aminopropionate,
methyl N-(2-acetoxyethyl)-N-cyanomethyl-3-aminopropionate,
N-cyanomethyl-N-(2-hydroxyethyl)aminoacetoneitrile,
15 N-(2-acetoxyethyl)-N-(cyanomethyl)aminoacetoneitrile,
N-cyanomethyl-N-(2-formyloxyethyl)aminoacetoneitrile,
N-cyanomethyl-N-(2-methoxyethyl)aminoacetoneitrile,
N-cyanomethyl-N-[2-(methoxymethoxy)ethyl]aminoacetoneitrile,
N-cyanomethyl-N-(3-hydroxy-1-propyl)aminoacetoneitrile,
20 N-(3-acetoxy-1-propyl)-N-(cyanomethyl)aminoacetoneitrile,
N-cyanomethyl-N-(3-formyloxy-1-propyl)aminoacetoneitrile,
N,N-bis(cyanomethyl)aminoacetoneitrile,
1-pyrrolidinepropiononitrile, 1-piperidinepropiononitrile,
4-morpholinepropiononitrile, 1-pyrrolidineacetoneitrile,
25 1-piperidineacetoneitrile, 4-morpholineacetoneitrile,
cyanomethyl 3-diethylaminopropionate,
cyanomethyl N,N-bis(2-hydroxyethyl)-3-aminopropionate,
cyanomethyl N,N-bis(2-acetoxyethyl)-3-aminopropionate,
cyanomethyl N,N-bis(2-formyloxyethyl)-3-aminopropionate,
30 cyanomethyl N,N-bis(2-methoxyethyl)-3-aminopropionate,
cyanomethyl N,N-bis[2-(methoxymethoxy)ethyl]-3-aminopropionate,
2-cyanoethyl 3-diethylaminopropionate,
2-cyanoethyl N,N-bis(2-hydroxyethyl)-3-aminopropionate,
2-cyanoethyl N,N-bis(2-acetoxyethyl)-3-aminopropionate,
35 2-cyanoethyl N,N-bis(2-formyloxyethyl)-3-aminopropionate,
2-cyanoethyl N,N-bis(2-methoxyethyl)-3-aminopropionate,

2-cyanoethyl N,N-bis[2-(methoxymethoxy)ethyl]-3-amino-
propionate, cyanomethyl 1-pyrrolidinepropionate,
cyanomethyl 1-piperidinepropionate,
cyanomethyl 4-morpholinepropionate,
5 2-cyanoethyl 1-pyrrolidinepropionate,
2-cyanoethyl 1-piperidinepropionate, and
2-cyanoethyl 4-morpholinepropionate.

[0100]

The basic compound is preferably formulated in an
10 amount of 0.001 to 2 parts, and especially 0.01 to 1 part by
weight, per 100 parts by weight of the base resin. Less
than 0.001 part of the basic compound may fail to achieve
the desired effects thereof, while the use of more than 2
parts would result in too low a sensitivity.

15 [0101]

The dissolution inhibitor used as component (E) is
preferably selected from compounds possessing a weight
average molecular weight of 100 to 1,000 and having on the
molecule at least two phenolic hydroxyl groups, in which an
20 average of from 10 to 100 mol% of all the hydrogen atoms on
the phenolic hydroxyl groups are replaced with acid labile
groups.

[0102]

Illustrative examples of the dissolution inhibitor
25 which are useful herein include
bis(4-(2'-tetrahydropyranyloxy)phenyl)methane,
bis(4-(2'-tetrahydrofuranyloxy)phenyl)methane,
bis(4-tert-butoxyphenyl)methane,
bis(4-tert-butoxycarbonyloxyphenyl)methane,
30 bis(4-tert-butoxycarbonylmethyloxyphenyl)methane,
bis(4-(1'-ethoxyethoxy)phenyl)methane,
bis(4-(1'-ethoxypropyloxy)phenyl)methane,
2,2-bis(4'-(2"-tetrahydropyranyloxy))propane,
2,2-bis(4'-(2"-tetrahydrofuranyloxy)phenyl)propane,
35 2,2-bis(4'-tert-butoxyphenyl)propane,
2,2-bis(4'-tert-butoxycarbonyloxyphenyl)propane,
2,2-bis(4-tert-butoxycarbonylmethyloxyphenyl)propane,

2,2-bis(4'-(1"-ethoxyethoxy)phenyl)propane,
2,2-bis(4'-(1"-ethoxypropyloxy)phenyl)propane,
tert-butyl 4,4-bis(4'-(2"-tetrahydropyranyloxy)phenyl)-
valerate,
5 tert-butyl 4,4-bis(4'-(2"-tetrahydrofuranyloxy)phenyl)-
valerate,
tert-butyl 4,4-bis(4'-tert-butoxyphenyl)valerate,
tert-butyl 4,4-bis(4-tert-butoxycarbonyloxyphenyl)valerate,
tert-butyl 4,4-bis(4'-tert-butoxycarbonylmethyloxyphenyl)-
10 valerate,
tert-butyl 4,4-bis(4'-(1"-ethoxyethoxy)phenyl)valerate,
tert-butyl 4,4-bis(4'-(1"-ethoxypropyloxy)phenyl)valerate,
tris(4-(2'-tetrahydropyranyloxy)phenyl)methane,
tris(4-(2'-tetrahydrofuranyloxy)phenyl)methane,
15 tris(4-tert-butoxyphenyl)methane,
tris(4-tert-butoxycarbonyloxyphenyl)methane,
tris(4-tert-butoxycarbonyloxymethylphenyl)methane,
tris(4-(1'-ethoxyethoxy)phenyl)methane,
tris(4-(1'-ethoxypropyloxy)phenyl)methane,
20 1,1,2-tris(4'-(2"-tetrahydropyranyloxy)phenyl)ethane,
1,1,2-tris(4'-(2"-tetrahydrofuranyloxy)phenyl)ethane,
1,1,2-tris(4'-tert-butoxyphenyl)ethane,
1,1,2-tris(4'-tert-butoxycarbonyloxyphenyl)ethane,
1,1,2-tris(4'-tert-butoxycarbonylmethyloxyphenyl)ethane,
25 1,1,2-tris(4'-(1'-ethoxyethoxy)phenyl)ethane, and
1,1,2-tris(4'-(1'-ethoxypropyloxy)phenyl)ethane.

[0103]

The compounds serving as dissolution inhibitor have a
weight average molecular weight of 100 to 1,000, preferably
30 150 to 800.

An appropriate amount of the dissolution inhibitor is
0 to 50 parts, preferably 5 to 50 parts, and especially 10
to 30 parts by weight per 100 parts by weight of the base
resin. Less amounts of the dissolution inhibitor may fail
35 to yield an improved resolution, whereas too much amounts
would lead to slimming of the patterned film, and thus a

decline in resolution. The inhibitor may be used singly or as a mixture of two or more thereof.

[0104]

The resist composition of the invention may include
5 optional ingredients, typically a surfactant which is commonly used for improving the coating characteristics. Optional ingredients may be added in conventional amounts so long as this does not compromise the objects of the invention.

10 [0105]

Illustrative, non-limiting, examples of the surfactant include nonionic surfactants, for example, polyoxyethylene alkyl ethers such as polyoxyethylene lauryl ether, polyoxyethylene stearyl ether, polyoxyethylene cetyl ether,
15 and polyoxyethylene oleyl ether, polyoxyethylene alkylaryl ethers such as polyoxyethylene octylphenol ether and polyoxyethylene nonylphenol ether, polyoxyethylene polyoxypropylene block copolymers, sorbitan fatty acid esters such as sorbitan monolaurate, sorbitan monopalmitate,
20 and sorbitan monostearate, and polyoxyethylene sorbitan fatty acid esters such as polyoxyethylene sorbitan monolaurate, polyoxyethylene sorbitan monopalmitate, polyoxyethylene sorbitan monostearate, polyoxyethylene sorbitan trioleate, and polyoxyethylene sorbitan
25 tristearate; fluorochemical surfactants such as EFTOP EF301, EF303 and EF352 (Tohkem Products Co., Ltd.), Megaface F171, F172 and F173 (Dai-Nippon Ink & Chemicals, Inc.), Fluorad FC430 and FC431 (Sumitomo 3M Co., Ltd.), Asahiguard AG710, Surflon S-381, S-382, SC101, SC102, SC103, SC104, SC105,
30 SC106, Surfynol E1004, KH-10, KH-20, KH-30 and KH-40 (Asahi Glass Co., Ltd.); organosiloxane polymers KP341, X-70-092 and X-70-093 (Shin-Etsu Chemical Co., Ltd.), acrylic acid or methacrylic acid Polyflow No. 75 and No. 95 (Kyo-eisha Ushi Kagaku Kogyo Co., Ltd.). Inter alia, FC430, Surflon S-381,
35 Surfynol E1004, KH-20 and KH-30 are preferred. These surfactants may be used alone or in admixture.

[0106]

Pattern formation using the resist composition of the invention may be carried out by a known lithographic technique. For example, the resist composition may be applied onto a substrate such as a silicon wafer by spin coating or the like to form a resist film having a thickness of 0.1 to 1.0 μm , which is then pre-baked on a hot plate at 60 to 200°C for 10 seconds to 10 minutes, and preferably at 80 to 150°C for 1/2 to 5 minutes. A patterning mask having the desired pattern may then be placed over the resist film, and the film exposed through the mask to an electron beam or to high-energy radiation such as deep-UV rays, excimer laser beams, or x-rays in a dose of about 1 to 200 mJ/cm^2 , and preferably about 10 to 100 mJ/cm^2 , then post-exposure baked (PEB) on a hot plate at 60 to 150°C for 10 seconds to 5 minutes, and preferably at 80 to 130°C for 1/2 to 3 minutes. Finally, development may be carried out using as the developer an aqueous alkali solution, such as 0.1 to 5%, and preferably 2 to 3%, tetramethylammonium hydroxide (TMAH), this being done by a conventional method such as dipping, puddling, or spraying for a period of 10 seconds to 3 minutes, and preferably 30 seconds to 2 minutes. These steps result in the formation of the desired pattern on the substrate.

[0107]

Of the various types of high-energy radiation that may be used, the resist composition of the invention is best suited to micro-pattern formation with, in particular, deep-UV rays having a wavelength of 254 to 120 nm, an excimer laser, especially ArF laser (193 nm), F_2 laser (157 nm), Kr_2 laser (146 nm), KrAr laser (134 nm) or Ar_2 laser (126 nm), x-rays, or an electron beam. Recommended is exposure to high-energy radiation in a wavelength band of 100 to 180 nm or 1 to 30 nm, specifically F_2 laser beam, Ar_2 laser beam or soft x-ray. The desired pattern may not be obtainable outside the upper and lower limits of the above range.

[0108]

[Effect of the Invention]

The resist composition of the invention is sensitive to high-energy radiation, maintains high transparency at a wavelength of up to 200 nm, and has improved alkali dissolution contrast and plasma etching resistance. These features permit the inventive resist composition to easily form a finely defined pattern having sidewalls perpendicular to the substrate and a high aspect ratio through F₂ laser exposure, making the resist ideal as a micropatterning material in VLSI fabrication.

[0109]

[EXAMPLE]

Synthesis Examples of sulfonate compound and polymers, and evaluation of resist compositions are given below by way of illustration, although the invention is not limited to the following Examples.

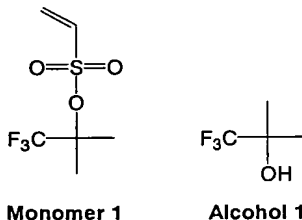
[0110]

[Monomer Synthesis Example 1] Synthesis of Monomer 1

Into a flask were admitted 40 g of dichloromethane, 10.0 g of Alcohol 1 shown below, and 13.0 g of pyridine. While the flask was immersed in an ice bath to keep the internal temperature below 10°C, 13.36 g of chloroethanesulfonyl chloride was added dropwise to the flask from a dropping funnel. The dropwise addition was followed by 2 hours of stirring. Conventional post treatment was carried out. The resulting oily matter was purified by silica gel chromatography, obtaining 10.9 g of Monomer 1. The yield was 64%.

[0111]

[Formula 45]



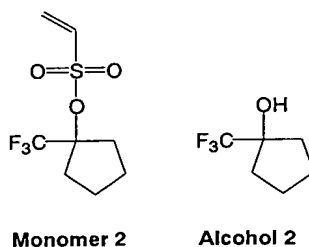
[0112]

[Monomer Synthesis Example 2] Synthesis of Monomer 2

Into a flask were admitted 40 g of dichloromethane,
10.0 g of Alcohol 2 shown below, and 10.8 g of pyridine.
5 While the flask was immersed in an ice bath to keep the
internal temperature below 10°C, 11.11 g of
chloroethanesulfonyl chloride was added dropwise to the
flask from a dropping funnel. The dropwise addition was
followed by 2 hours of stirring. Conventional post
10 treatment was carried out. The resulting oily matter was
purified by silica gel chromatography, obtaining 11.4 g of
Monomer 2. The yield was 72%.

[0113]

[Formula 46]



15 [0114]

[Polymer Synthesis Example 1] Copolymerization of Monomer 1,
Monomer 3 and Monomer 3 (0.4:0.2:0.4)

A 300-ml flask was charged with 5.47 g of Monomer 1,
6.55 g of Monomer 3, shown below, and 7.98 g of Monomer 4,
20 shown below, which were dissolved in 5.0 g of 1,4-dioxane.
The system was fully purged of oxygen, charged with 0.51 g
of the initiator AIBN, and heated at 65°C at which
polymerization reaction took place for 24 hours.

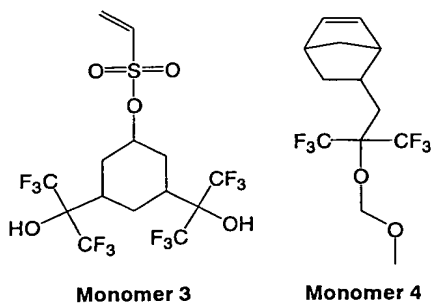
[0115]

25 The polymer thus obtained was worked up by pouring the
reaction mixture into 1 liter of hexane whereupon the
polymer precipitated. The procedure of dissolving the
polymer in tetrahydrofuran (THF for tetrahydrofuran, herein
after) and pouring in 1 liter of hexane for precipitation
30 was repeated twice, after which the polymer was separated

and dried. There was obtained 12.5 g of a white polymer, which was found to have a weight average molecular weight of 6,100 as measured by the light scattering method, and a dispersity (Mw/Mn) of 1.4 as determined from the GPC elution curve. On ¹H-NMR analysis, the polymer was found to consist of respective units derived from Monomer 1:Monomer 3:Monomer 4 in a molar ratio of 0.37:0.19:0.44.

[0116]

[Formula 47]



[0117]

[Polymer Synthesis Example 2] Copolymerization of Monomer 1, Monomer 5 and Monomer 6 (0.3:0.3:0.4)

A 300-ml flask was charged with 5.60 g of Monomer 1, 5.03 g of Monomer 5, shown below, and 9.37 g of Monomer 6, shown below, which were dissolved in 5.0 g of 1,4-dioxane. The system was fully purged of oxygen, charged with 0.70 g of the initiator AIBN, and heated at 65°C at which polymerization reaction took place for 24 hours.

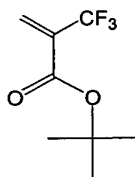
[0118]

The polymer thus obtained was worked up by pouring the reaction mixture into 1 liter of hexane whereupon the polymer precipitated. The procedure of dissolving the polymer in THF and pouring in 1 liter of hexane for precipitation was repeated twice, after which the polymer was separated and dried. There was obtained 11.7 g of a white polymer, which was found to have a weight average molecular weight of 6,800 as measured by the light scattering method, and a dispersity (Mw/Mn) of 1.4 as determined from the GPC elution curve. On ¹H-NMR analysis,

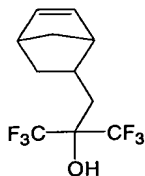
the polymer was found to consist of respective units derived from Monomer 1:Monomer 5:Monomer 6 in a molar ratio of 0.29:0.31:0.40.

[0119]

5 [Formula 48]



Monomer 5



Monomer 6

[0120]

[Polymer Synthesis Example 3] Copolymerization of Monomer 1, Monomer 5 and Monomer 7 (0.3:0.3:0.4)

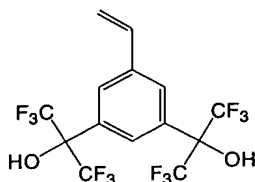
10 A 300-ml flask was charged with 4.38 g of Monomer 1, 3.94 g of Monomer 5 and 11.7 g of Monomer 7, shown below, which were dissolved in 5.0 g of 1,4-dioxane. The system was fully purged of oxygen, charged with 0.55 g of the initiator AIBN, and heated at 65°C at which polymerization
15 reaction took place for 24 hours.

[0121]

The polymer thus obtained was worked up by pouring the reaction mixture into 1 liter of hexane whereupon the polymer precipitated. The procedure of dissolving the
20 polymer in THF and pouring in 1 liter of hexane for precipitation was repeated twice, after which the polymer was separated and dried. There was obtained 12.9 g of a white polymer, which was found to have a weight average molecular weight of 9,800 as measured by the light
25 scattering method, and a dispersity (Mw/Mn) of 1.4 as determined from the GPC elution curve. On ¹H-NMR analysis, the polymer was found to consist of respective units derived from Monomer 1:Monomer 5:Monomer 7 in a molar ratio of 0.30:0.31:0.39.

[0122]

[Formula 49]



Monomer 7

[0123]

5 [Polymer Synthesis Example 4] Copolymerization of Monomer 2, Monomer 3 and Monomer 4 (0.4:0.2:0.4)

A 300-ml flask was charged with 5.93 g of Monomer 2, 6.34 g of Monomer 3 and 7.73 g of Monomer 4, which were dissolved in 5.0 g of 1,4-dioxane. The system was fully
10 purged of oxygen, charged with 0.50 g of the initiator AIBN, and heated at 65°C at which polymerization reaction took place for 24 hours.

[0124]

The polymer thus obtained was worked up by pouring the
15 reaction mixture into 1 liter of hexane whereupon the polymer precipitated. The procedure of dissolving the polymer in THF and pouring in 1 liter of hexane for precipitation was repeated twice, after which the polymer was separated and dried. There was obtained 13.9 g of a
20 white polymer, which was found to have a weight average molecular weight of 6,800 as measured by the light scattering method, and a dispersity (M_w/M_n) of 1.4 as determined from the GPC elution curve. On ¹H-NMR analysis, the polymer was found to consist of respective units derived
25 from Monomer 2:Monomer 3:Monomer 4 in a molar ratio of 0.36:0.19:0.45.

[0125]

[Polymer Synthesis Example 5] Copolymerization of Monomer 2, Monomer 5 and Monomer 6 (0.3:0.3:0.4)

30 A 300-ml flask was charged with 6.06 g of Monomer 2, 4.87 g of Monomer 5 and 9.07 g of Monomer 6, which were dissolved in 5.0 g of 1,4-dioxane. The system was fully

purged of oxygen, charged with 0.68 g of the initiator AIBN, and heated at 65°C at which polymerization reaction took place for 24 hours.

[0126]

5 The polymer thus obtained was worked up by pouring the reaction mixture into 1 liter of hexane whereupon the polymer precipitated. The procedure of dissolving the polymer in THF and pouring in 1 liter of hexane for precipitation was repeated twice, after which the polymer
10 was separated and dried. There was obtained 14.2 g of a white polymer, which was found to have a weight average molecular weight of 6,900 as measured by the light scattering method, and a dispersity (M_w/M_n) of 1.4 as determined from the GPC elution curve. On ^1H -NMR analysis,
15 the polymer was found to consist of respective units derived from Monomer 2:Monomer 5:Monomer 6 in a molar ratio of 0.28:0.32:0.40.

[0127]

[Polymer Synthesis Example 6] Copolymerization of Monomer 2,
20 Monomer 5 and Monomer 7 (0.3:0.3:0.4)

A 300-ml flask was charged with 4.78 g of Monomer 2, 3.84 g of Monomer 5 and 11.38 g of Monomer 7, which were dissolved in 5.0 g of 1,4-dioxane. The system was fully purged of oxygen, charged with 0.54 g of the initiator AIBN,
25 and heated at 65°C at which polymerization reaction took place for 24 hours.

[0128]

The polymer thus obtained was worked up by pouring the reaction mixture into 1 liter of hexane whereupon the
30 polymer precipitated. The procedure of dissolving the polymer in THF and pouring in 1 liter of hexane for precipitation was repeated twice, after which the polymer was separated and dried. There was obtained 13.6 g of a white polymer, which was found to have a weight average
35 molecular weight of 9,600 as measured by the light scattering method, and a dispersity (M_w/M_n) of 1.4 as determined from the GPC elution curve. On ^1H -NMR analysis,

the polymer was found to consist of respective units derived from Monomer 2:Monomer 5:Monomer 7 in a molar ratio of 0.29:0.30:0.41.

[0129]

5 [Evaluation]

Polymer transmittance measurement

Each polymer, 1 g, was thoroughly dissolved in 20 g of propylene glycol monomethyl ether acetate (PGMEA for propylene glycol monomethyl ether acetate, hereinafter), and
10 passed through a 0.2- μ m filter, obtaining a polymer solution.

[0130]

Comparative Polymer 1 is a monodisperse polyhydroxystyrene having a molecular weight of 10,000 and a dispersity (Mw/Mn) of 1.1 in which 30% of hydroxyl groups
15 are replaced by tetrahydropyranyl groups. Similarly, Comparative Polymer 2 is polymethyl methacrylate having a molecular weight of 15,000 and a dispersity (Mw/Mn) of 1.7; and Comparative Polymer 3 is a novolac polymer having a meta/para ratio of 40/60, a molecular weight of 9,000 and a
20 dispersity (Mw/Mn) of 2.5. The polymer solution is obtained from the above-described same procedure.

[0131]

The polymer solution was spin coated onto a MgF₂ substrate and baked on a hot plate at 100°C for 90 seconds,
25 forming a polymer film of 100 nm thick on the substrate. Using a vacuum ultraviolet spectrometer (VUV-200S by Nihon Bunko Co., Ltd.), the polymer film was measured for transmittance at 248 nm, 193 nm and 157 nm. The results are shown in Table 1. It is evident from Table 1 that resist
30 materials using the inventive polymers maintain sufficient transparency at the F₂ laser wavelength (157 nm).

[0132]

Table 1

Polymer	Transmittance (%) 248 nm	Transmittance (%) 193 nm	Transmittance (%) 157 nm
Polymer 1	99	93	72
Polymer 2	99	93	67
Polymer 3	99	10	63
Polymer 4	99	93	71
Polymer 5	99	93	66
Polymer 6	99	10	62
Comparative Polymer 1	90	5	15
Comparative Polymer 2	91	80	12
Comparative Polymer 3	82	6	17

[0133]

5 Resist preparation and exposure

Resist solutions were prepared in a conventional manner by dissolving amounts as shown in Table 2 of the polymer, photoacid generator, basic compound, and dissolution inhibitor in 1,000 parts of PGMEA.

10 On silicon wafers having a film of DUV-30 (Brewer Science) coated to a thickness of 85 nm, the resist solutions were spin coated, then baked on a hot plate at 120°C for 90 seconds to give resist films having a thickness of 100 nm.

15 [0134]

The resist films were exposed by means of an F₂ excimer laser exposure tool (VUVES-4500 by Litho Tech Japan Corp.) while varying the exposure dose. Immediately after exposure, the resist films were baked (PEB) at 120°C for 90
20 seconds and then developed for 60 seconds with a 2.38% aqueous solution of tetramethylammonium hydroxide. The film

thickness was measured in different dose areas. From the residual film thickness-to-dose relationship, the sensitivity (E_{th}) was determined as the exposure dose giving a film thickness 0. A γ value which was the slope ($\tan\theta$) of the characteristic curve was also determined.

[0135]

Separately, through a mask having a Cr pattern formed on a MgF_2 substrate, the resist film in close contact with the Cr pattern surface was exposed to a F_2 laser for effecting contact exposure. The exposure was followed by similar PEB and development, forming a pattern. A cross section of the pattern was observed under SEM, the ascertainable minimum pattern size giving a resolution.

Upon exposure to VUVES, the resist compositions within the scope of the invention exhibited high gamma values and high contrast and exerted the positive working effect that the film thickness decreased with an increasing exposure dose. The resolving power upon contact exposure was high.

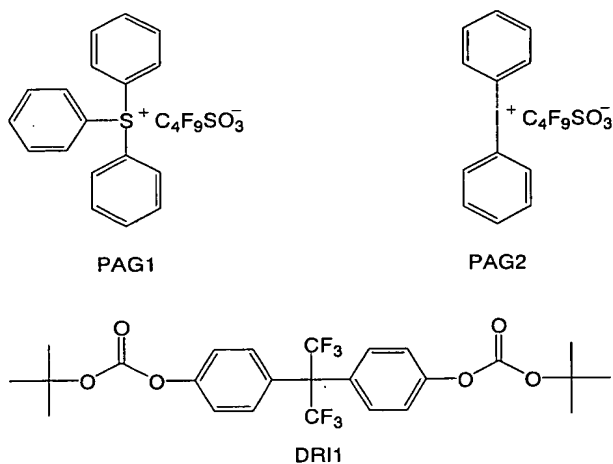
[0136]

Table 2

Polymer (pbw)	Photoacid generator (pbw)	Basic compound (pbw)	Dissolution inhibitor (pbw)	Solvent (pbw)	Eth, mJ/cm ²	γ
Polymer 1 (100)	PAG1 (4)	tributylamine (0.1)	-	PGMEA (1000)	18	8.9
Polymer 2 (100)	PAG1 (4)	tributylamine (0.1)	-	PGMEA (1000)	14	10.5
Polymer 3 (100)	PAG1 (4)	tributylamine (0.1)	-	PGMEA (1000)	12	10.9
Polymer 4 (100)	PAG1 (4)	tributylamine (0.1)	-	PGMEA (1000)	13	9.3
Polymer 5 (100)	PAG1 (4)	tributylamine (0.1)	-	PGMEA (1000)	11	10.8
Polymer 6 (100)	PAG1 (4)	tributylamine (0.1)	-	PGMEA (1000)	9	10.5
Polymer 2 (100)	PAG1 (4)	triethanolamine (0.1)	-	PGMEA (1000)	16	10.3
Polymer 2 (100)	PAG1 (4)	tributylamine (0.1)	DRI1 (10)	PGMEA (1000)	12	10.1
Polymer 2 (100)	PAG2 (4)	tributylamine (0.1)	-	PGMEA (1000)	10	12.9
Comparative Polymer 1 (100)	PAG1 (4)	triethanolamine (0.1)	-	PGMEA (1000)	non-sensitive, turned negative without film thickness decreasing to 0 nm	-

[0137]

5 [Formula 50]



[0138]

Dry etching test

A polymer solution was prepared by thoroughly dissolving 2 g in 10 g of PGMEA and passing the solution through a 0.2-micron size filter. The polymer solution was spin coated to a silicon substrate and baked to form a polymer film of 300 nm thick. The wafer having the polymer film formed thereon was subjected to dry etching under two sets of conditions. A first etching test with CHF_3/CF_4 gas was performed using a dry etching instrument TE-8500P by Tokyo Electron K.K. A second etching test with Cl_2/BCl_3 gas was performed using a dry etching instrument L-507D-L by Nichiden Anerba K.K. A difference in polymer film thickness before and after the etching test was determined. The etching conditions are shown in Table 3, and the results in Table 4.

It is evident from Table 4 that the resist compositions within the scope of the invention are fully resistant to dry etching.

[0139]

Table 3

	CHF_3/CF_4 gas	Cl_2/BCl_3 gas
Chamber pressure (Pa)	40.0	40.0
RF power (W)	1,300	300
Gap (mm)	9	9
Gas flow rate (ml/min)	CHF_3 : 30 CF_4 : 30 Ar: 100	Cl_2 : 30 BCl_3 : 30 CHF_3 : 100 O_2 : 2
Time (sec)	30	30

[0140]

Table 4

Polymer	CHF ₃ /CF ₄ gas etching rate (nm/min)	Cl ₂ /BCl ₃ gas etching rate (nm/min)
Polymer 1	220	280
Polymer 2	210	260
Polymer 3	170	200
Polymer 4	205	235
Polymer 5	190	225
Polymer 6	155	170

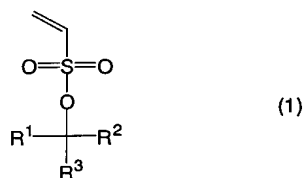
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[ABSTRACT]

[Means for Solution]

A sulfonate compound having the formula (1):

5 [Formula 1]



wherein R^1 to R^3 each are hydrogen, fluorine, or alkyl or fluorinated alkyl group, at least one of R^1 to R^3 contains fluorine.

[Effect]

10 The resist composition of the invention is sensitive to high-energy radiation, maintains high transparency at a wavelength of up to 200 nm, and has improved alkali dissolution contrast and plasma etching resistance.

[Selected Drawing] none